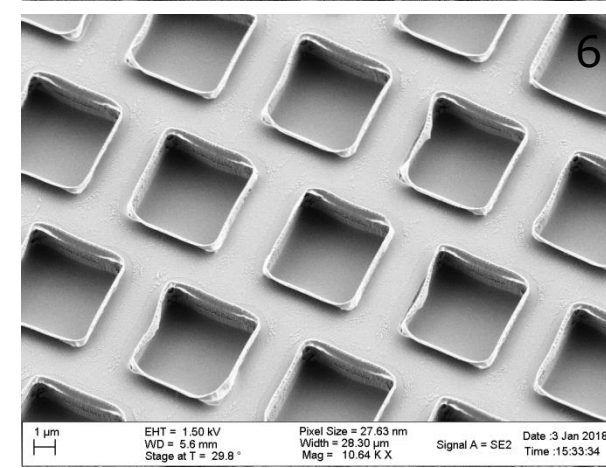
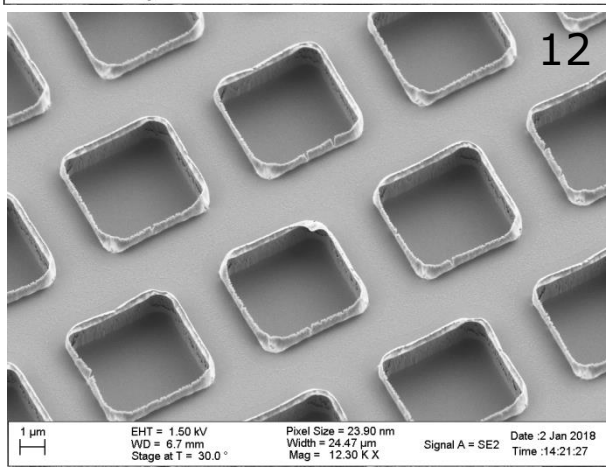
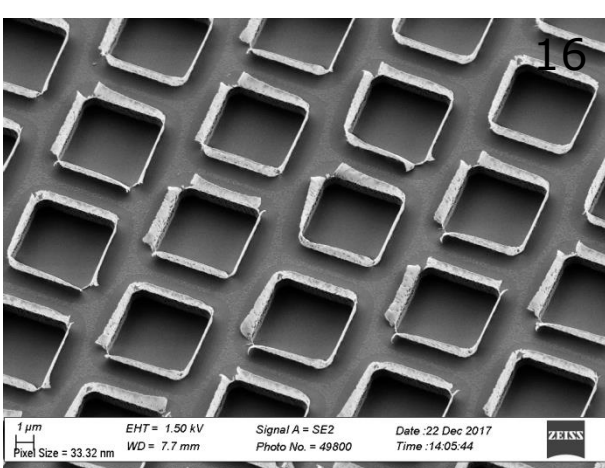
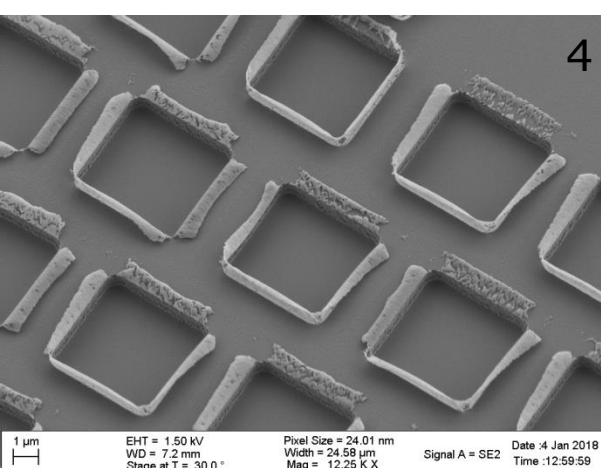
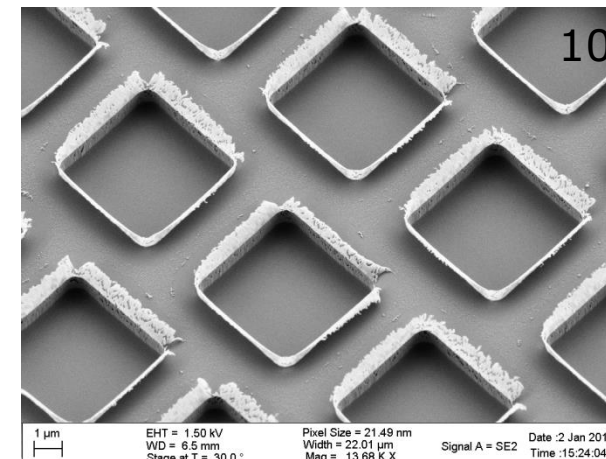
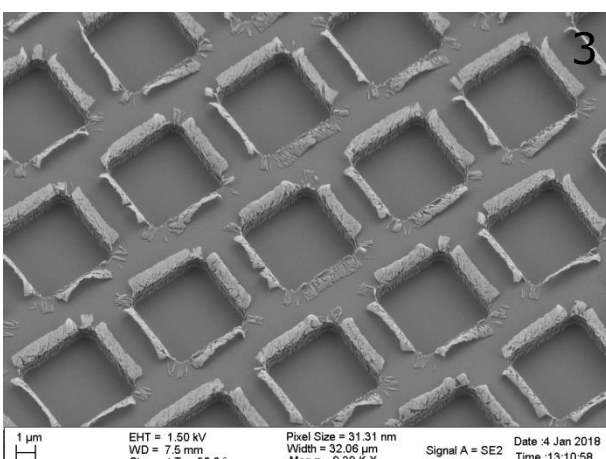
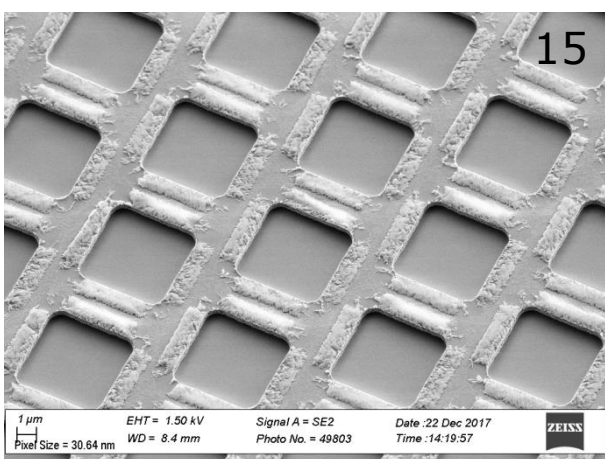
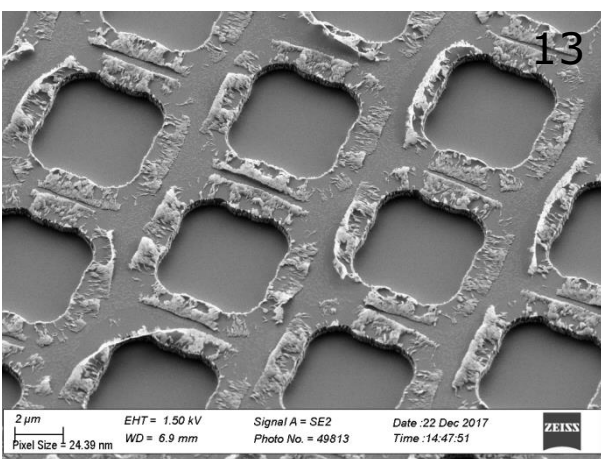
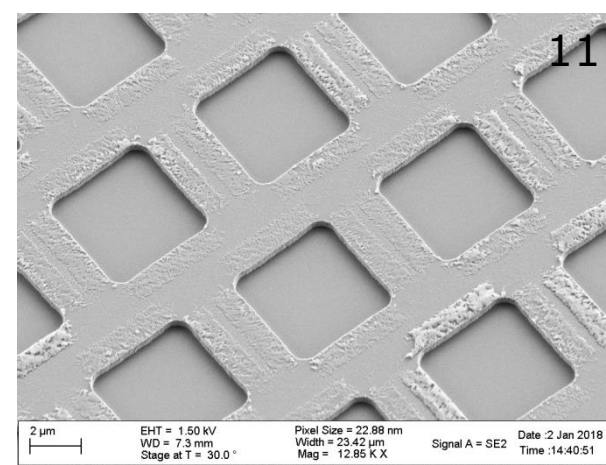
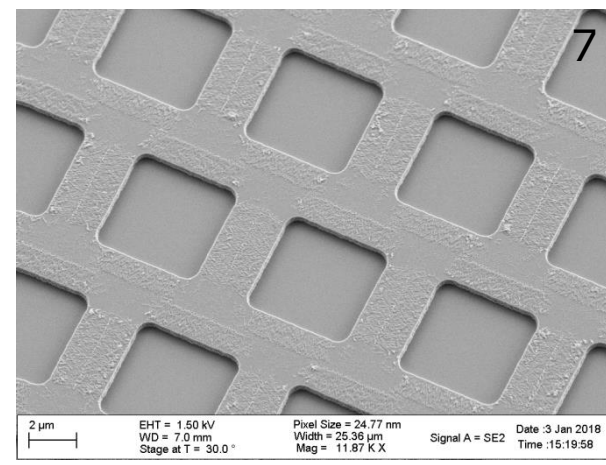
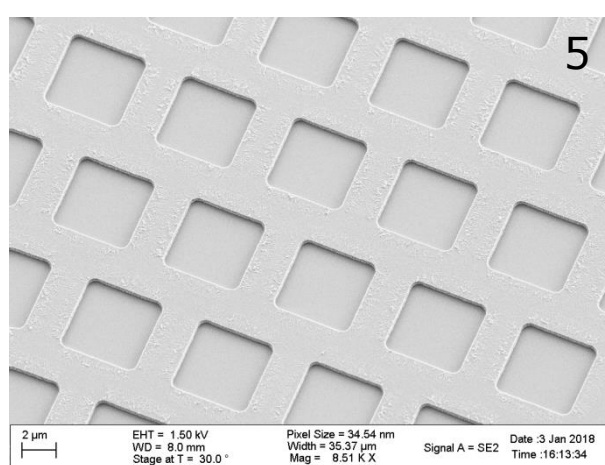
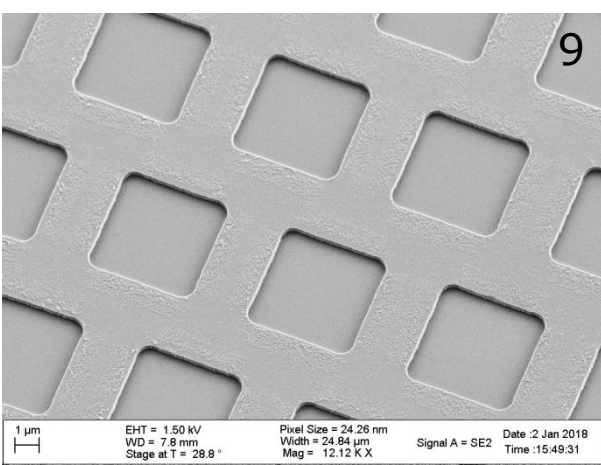
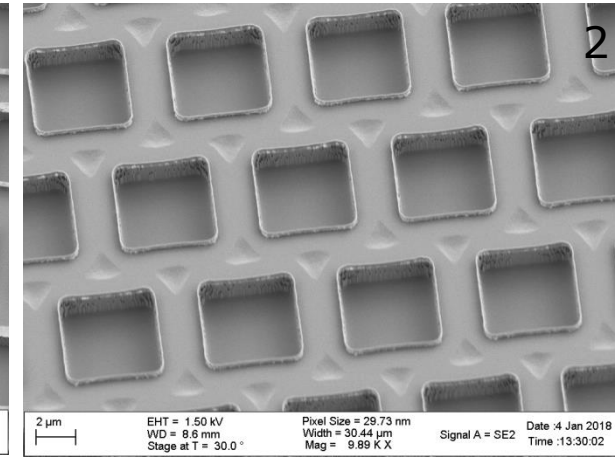
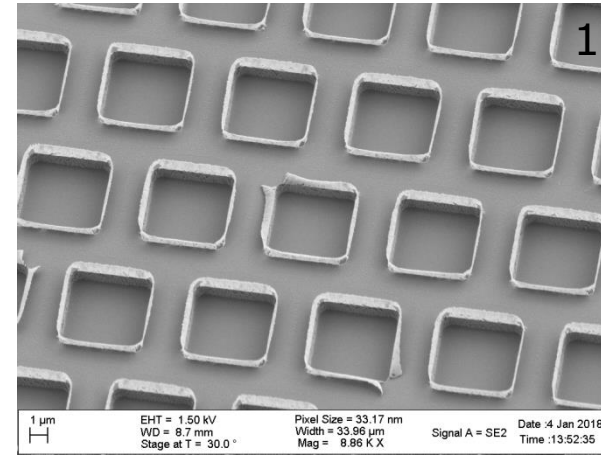
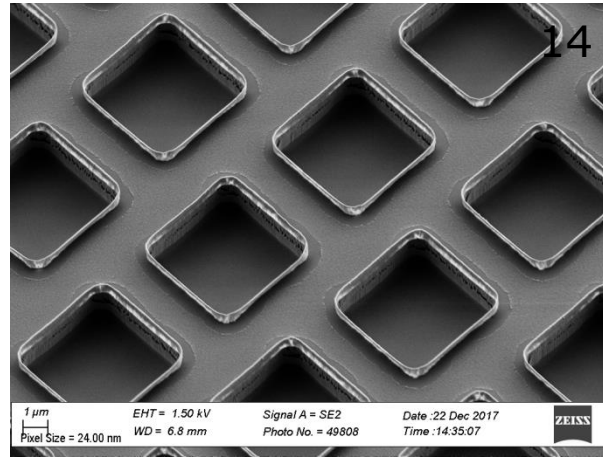
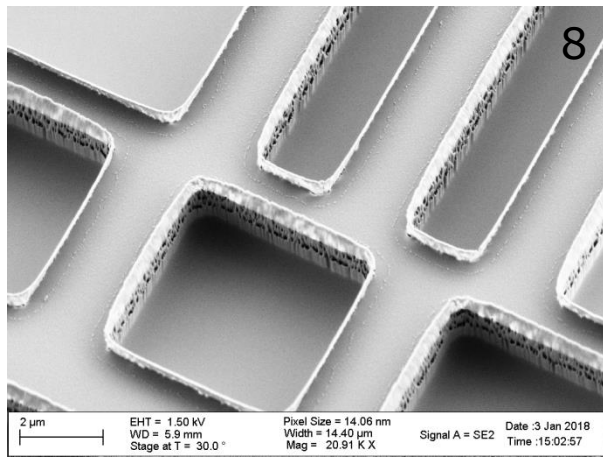


SiO₂ etch in RIE mode with the ASE

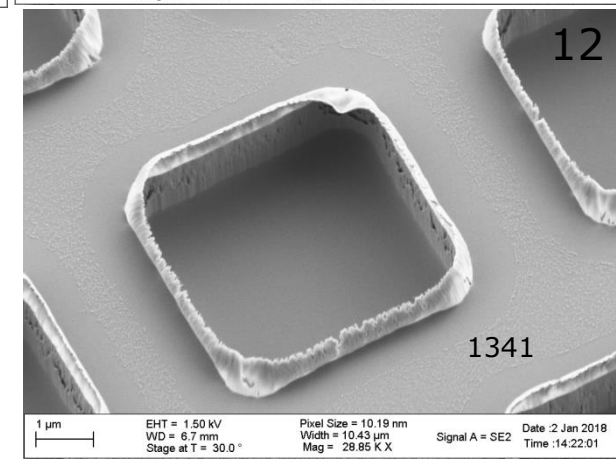
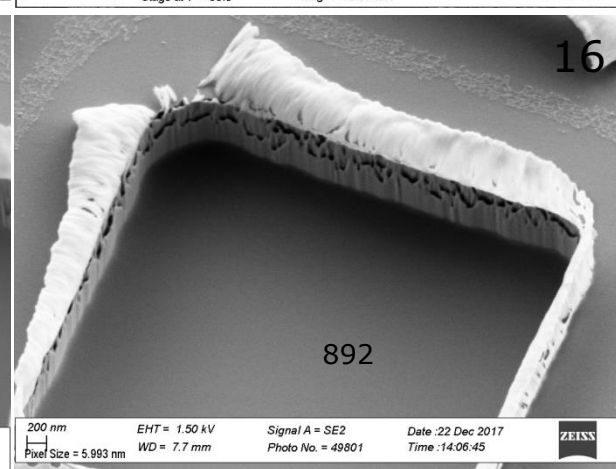
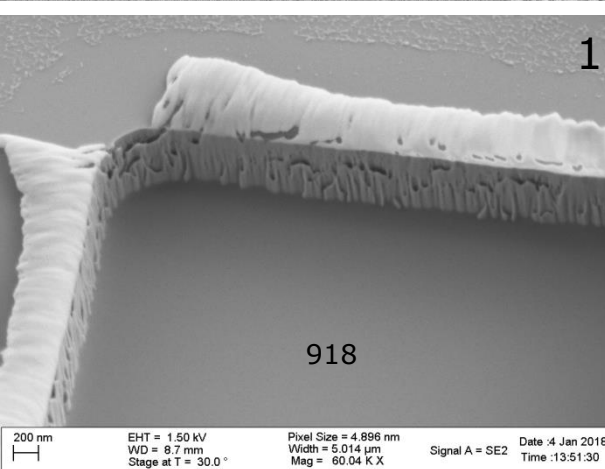
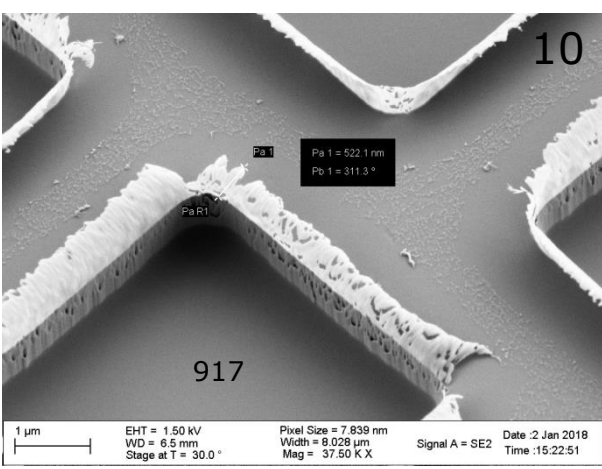
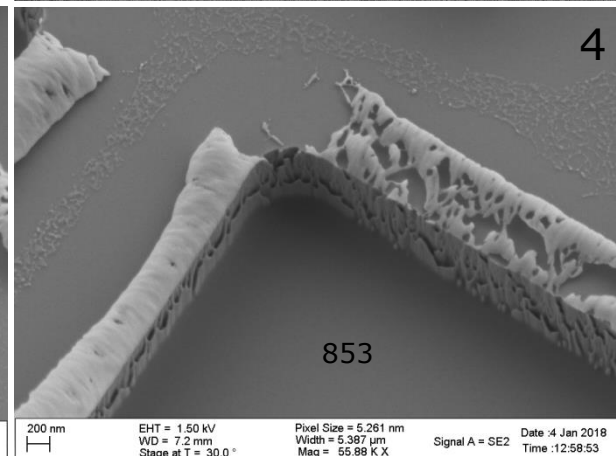
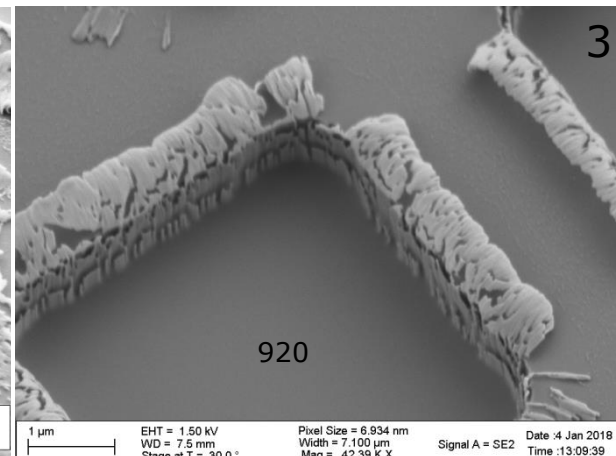
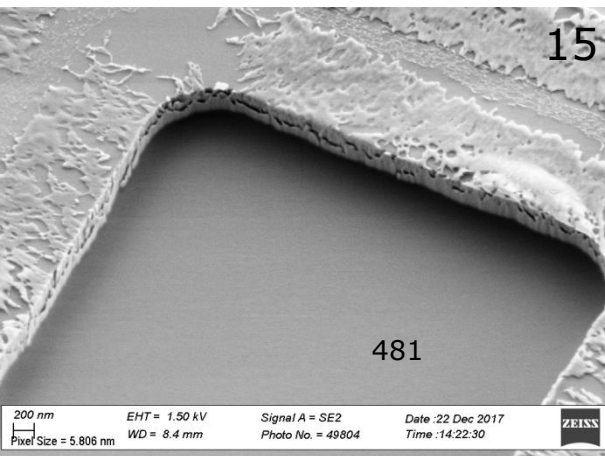
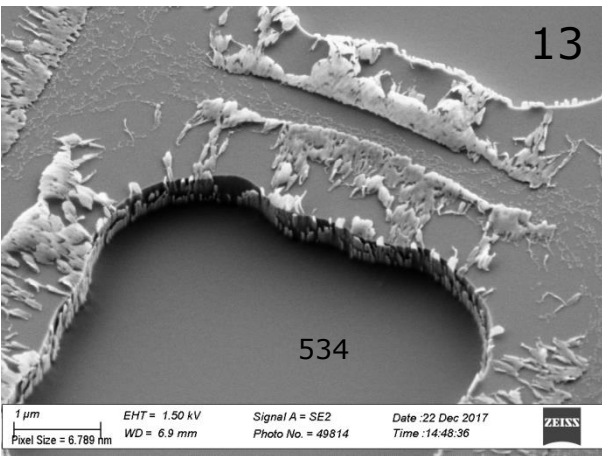
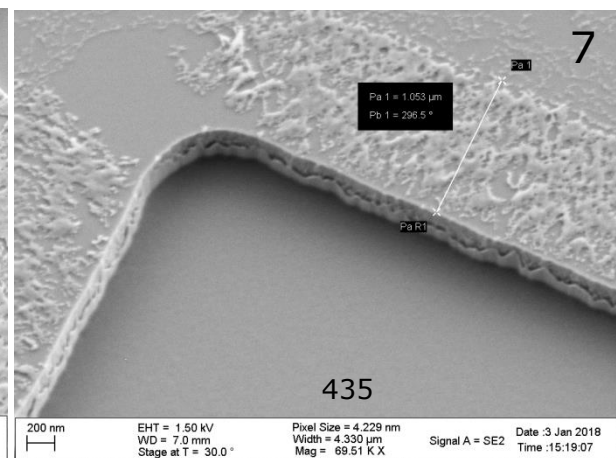
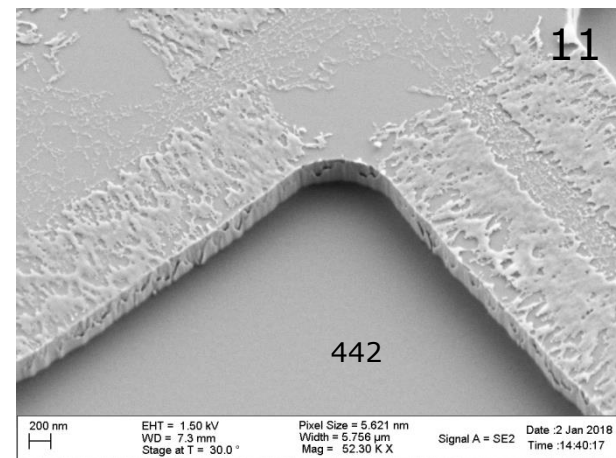
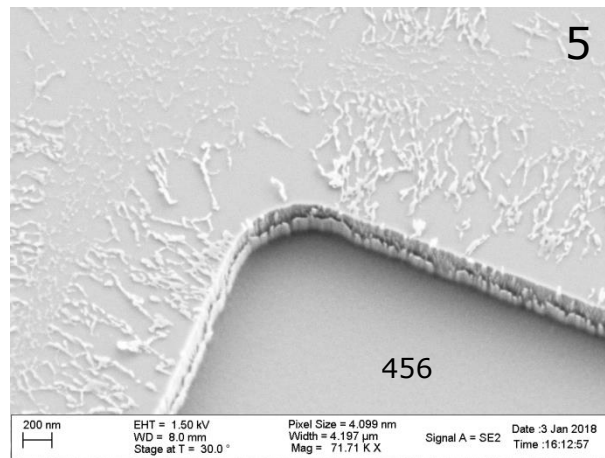
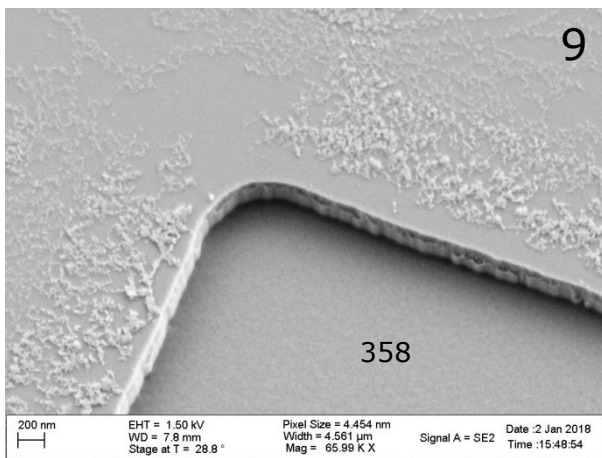
Comparison of redeposition on the resist sidewalls seen after a plasma ashing step. Results from a DOE described in LabAdviser@Nanolab.dtu.dk

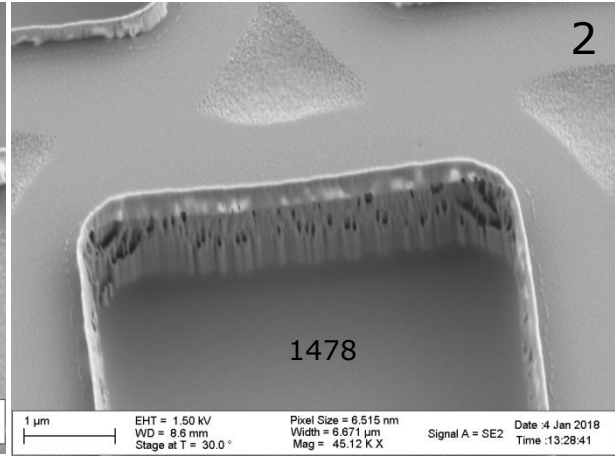
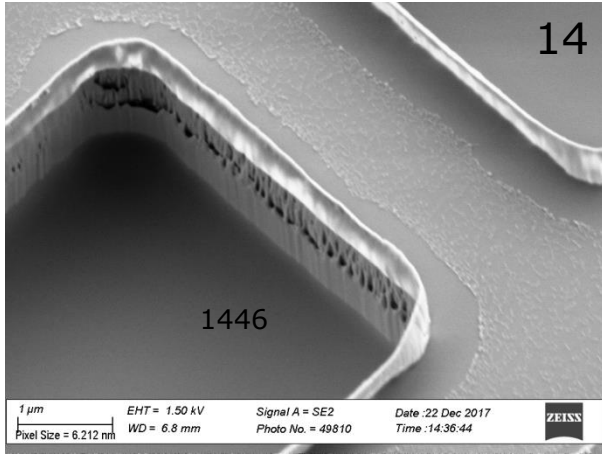
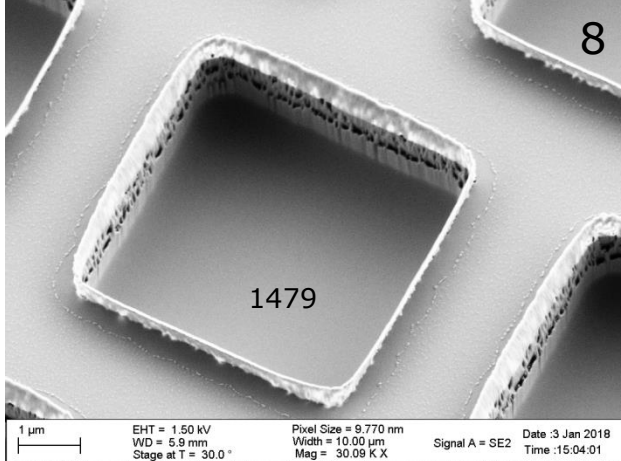
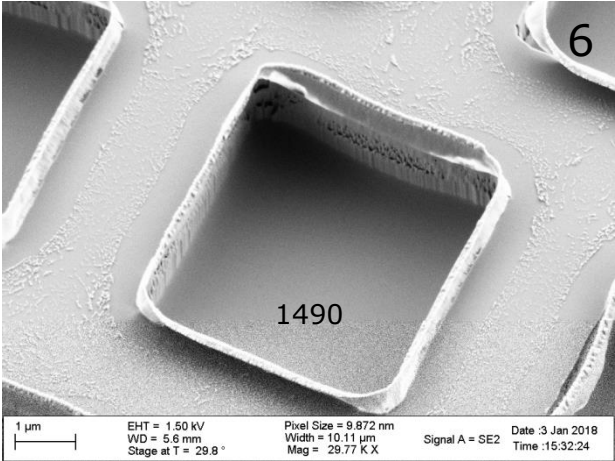
This work is done by Berit Herstrøm @DTU Nanolab in 2017/2018





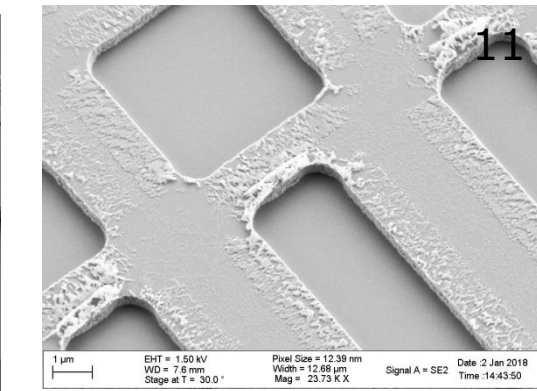
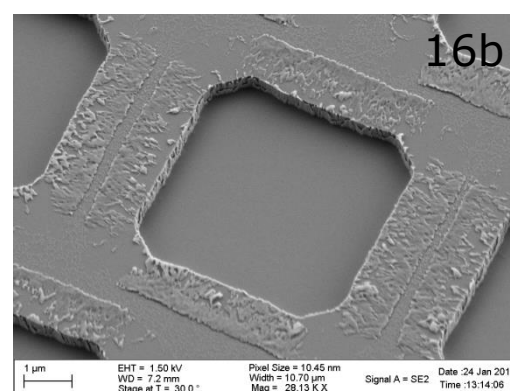
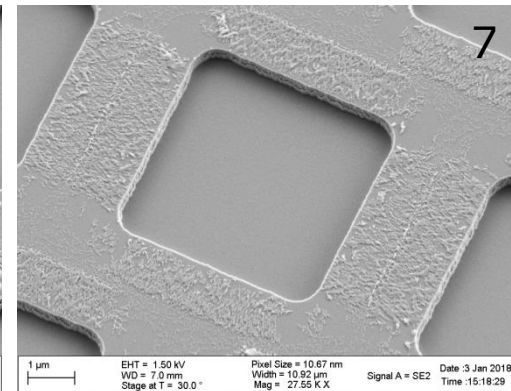
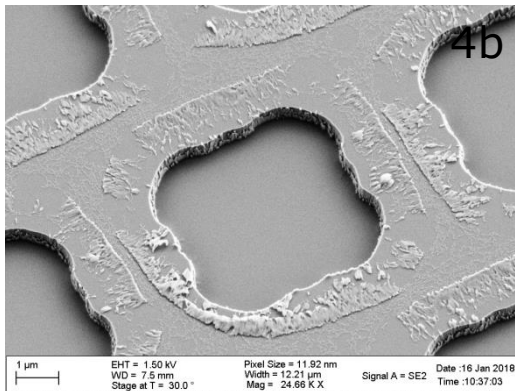
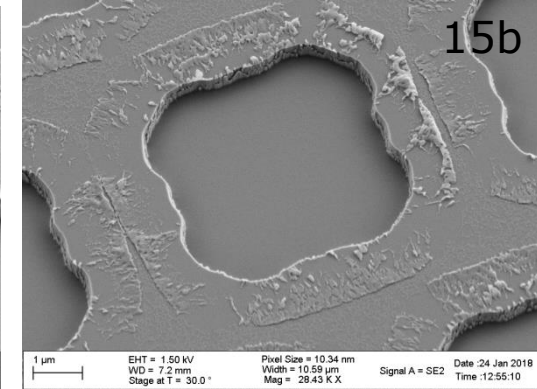
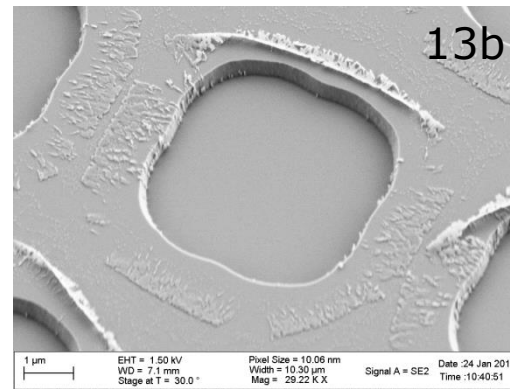
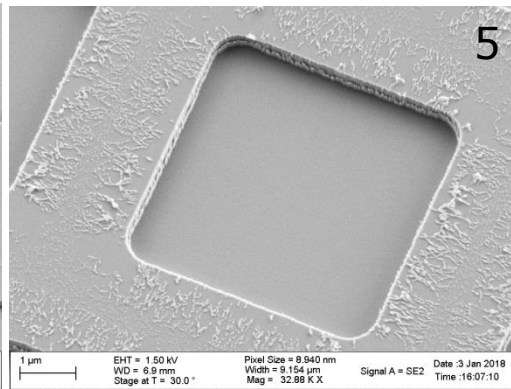
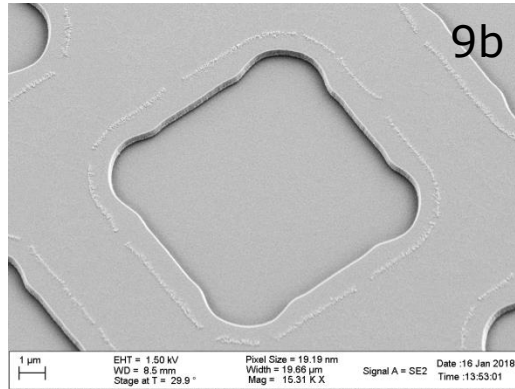
The numbers 1-16 on the images refers to the experiment number in the DOE

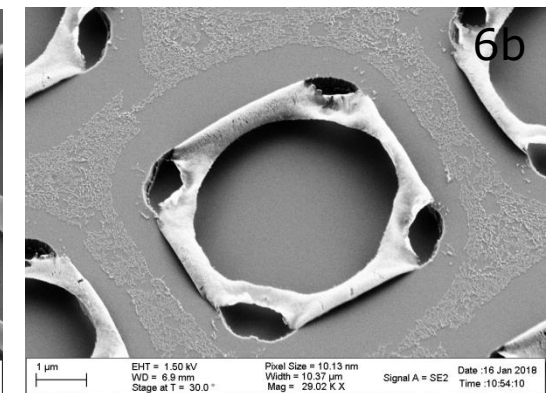
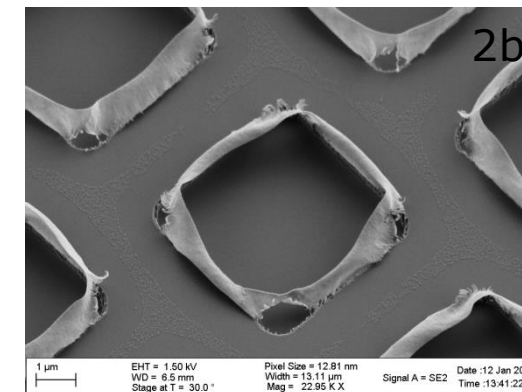
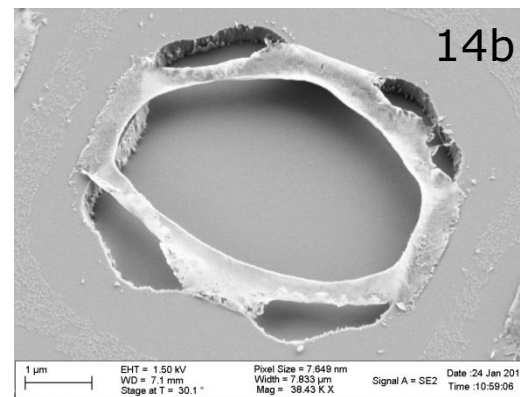
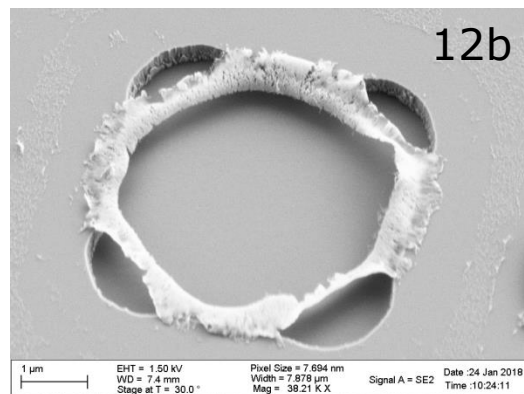
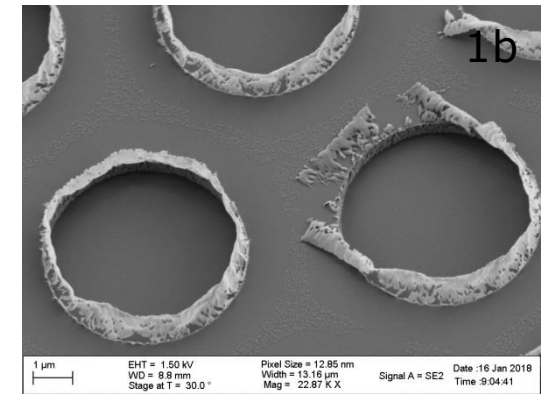
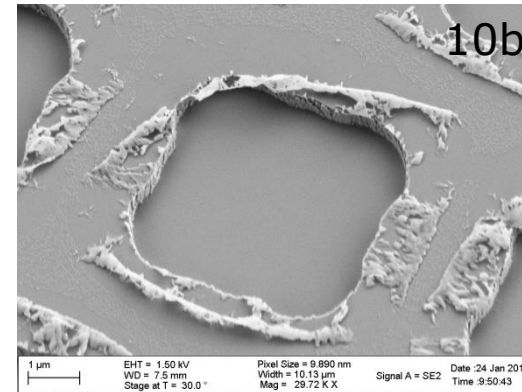
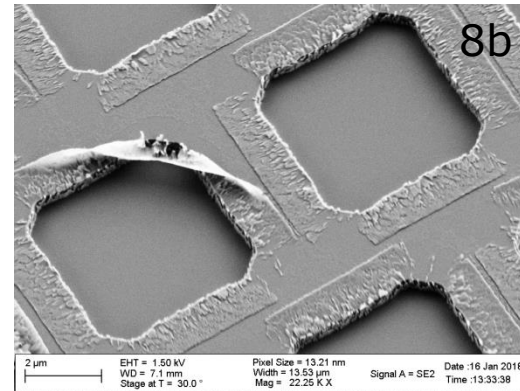
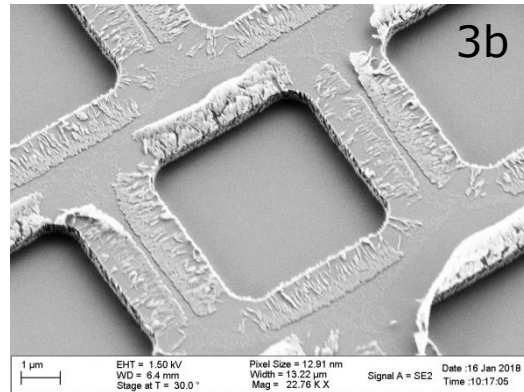


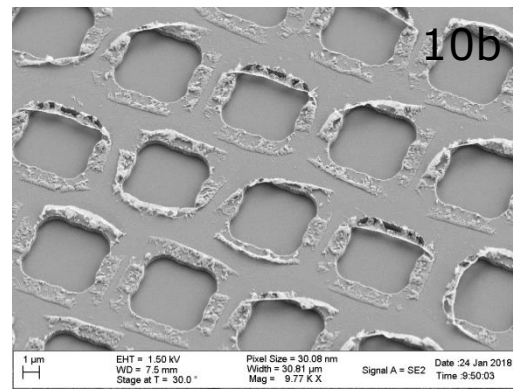
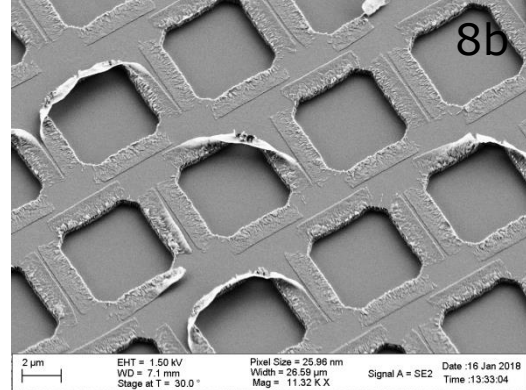
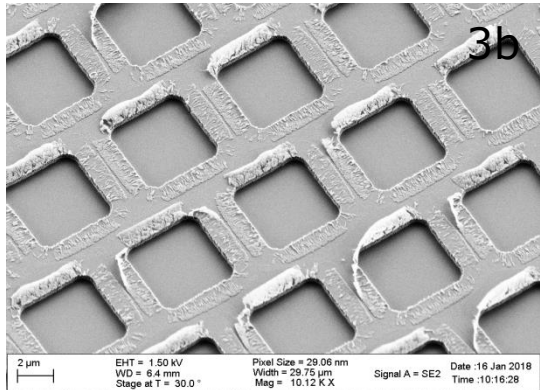
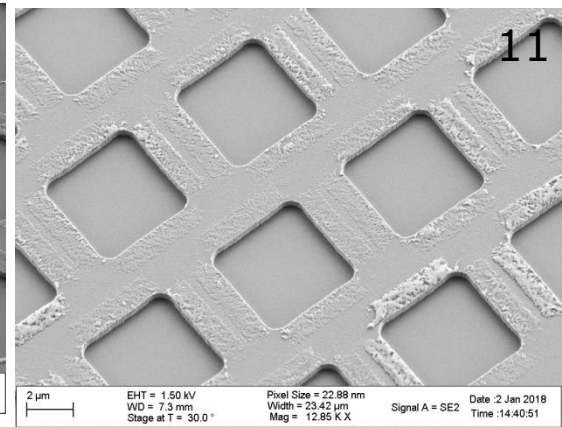
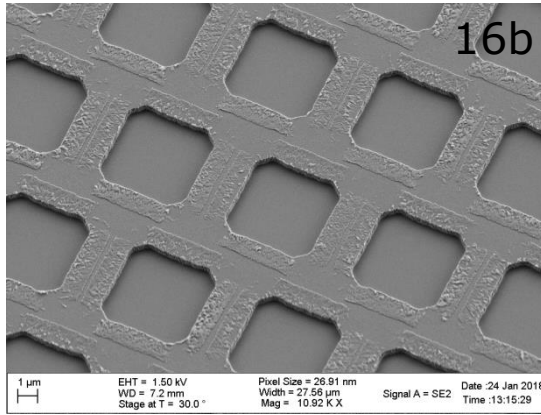
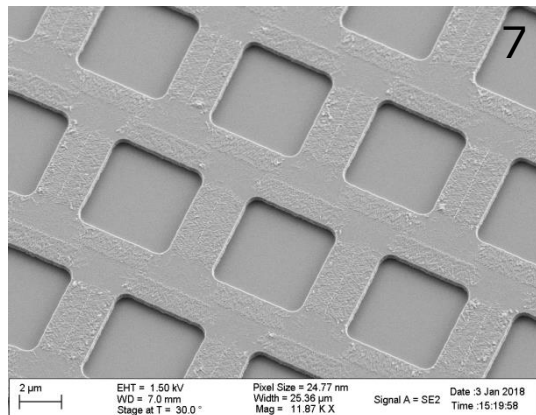
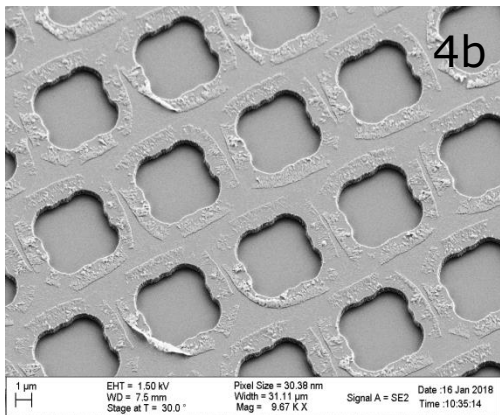
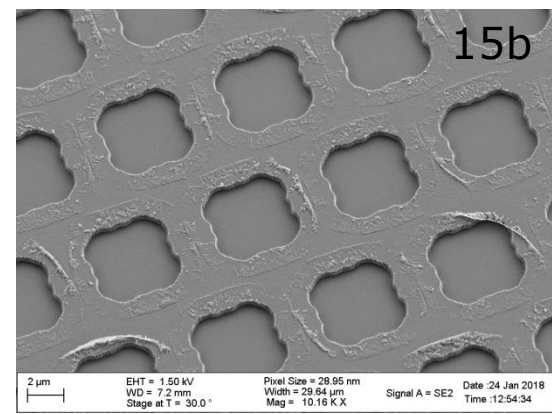
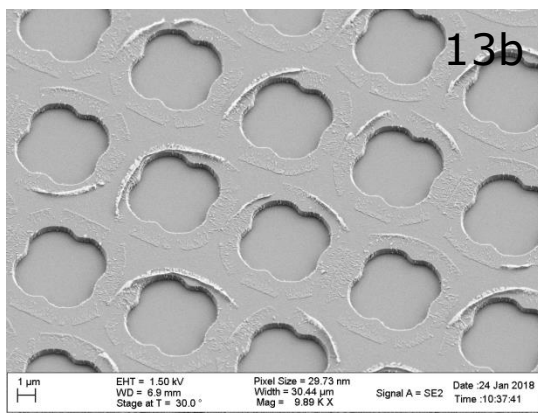
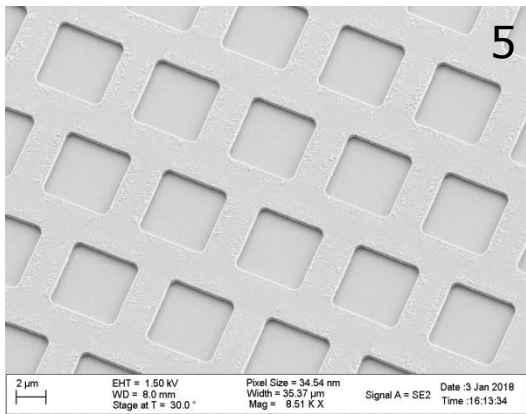
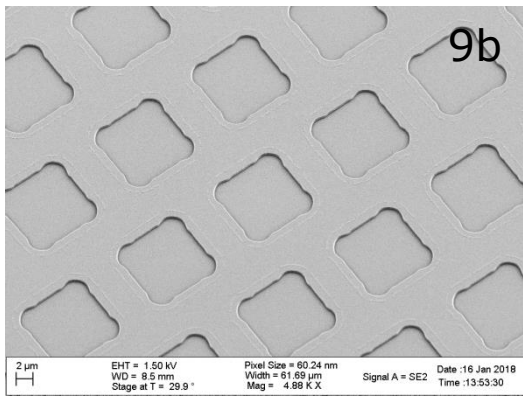


Approximately same etch depth

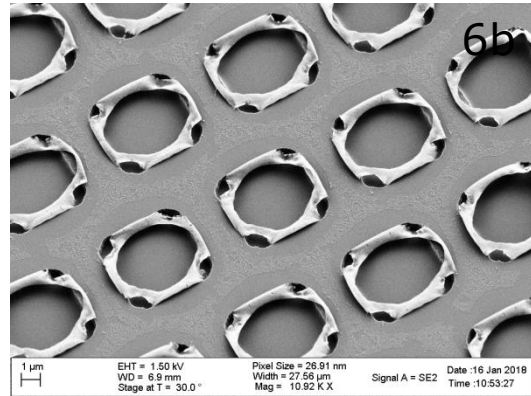
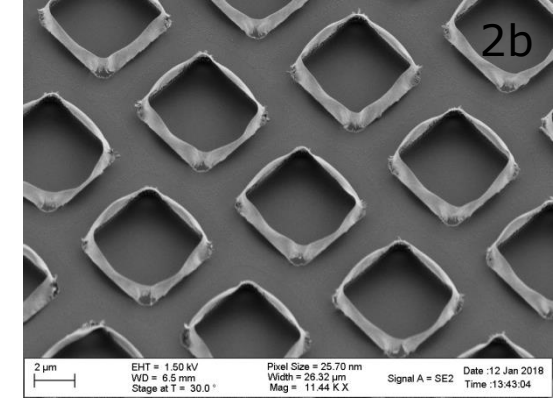
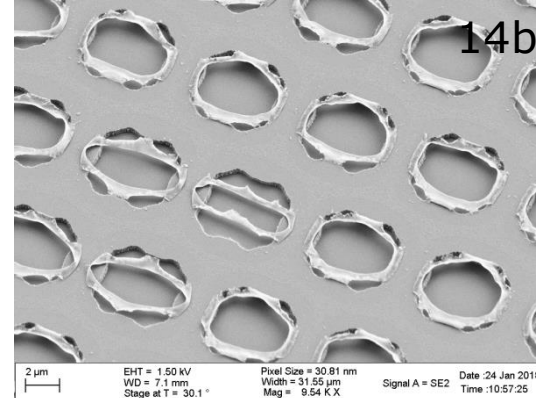
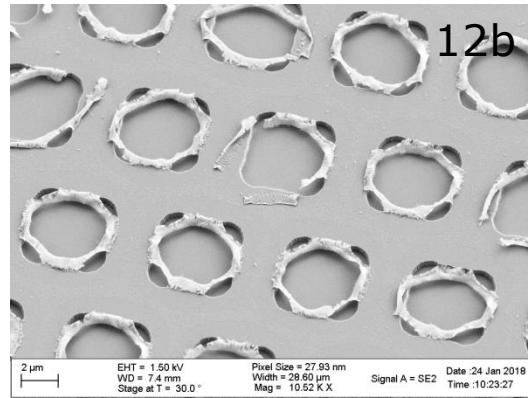
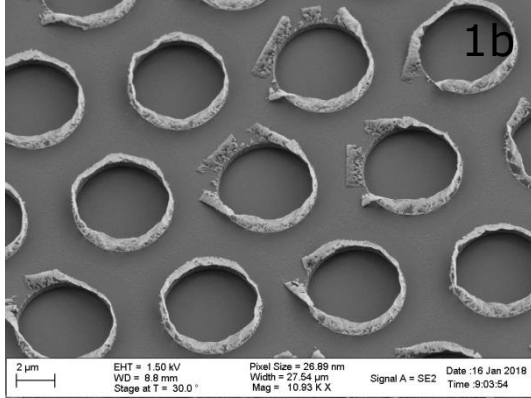
Sorted after the amount of re-deposition





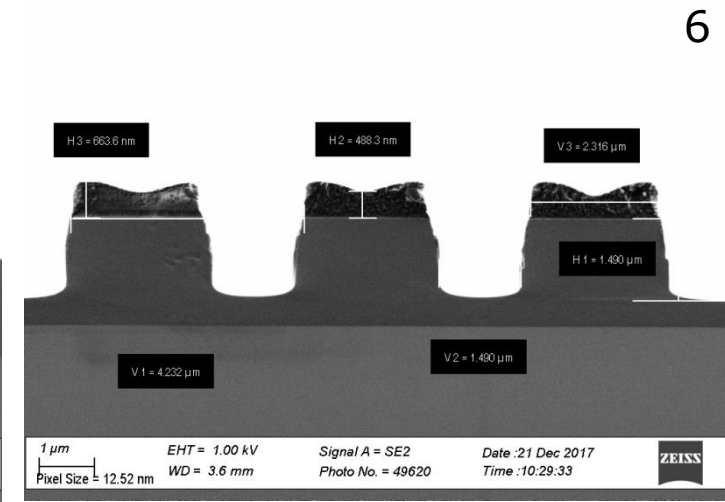
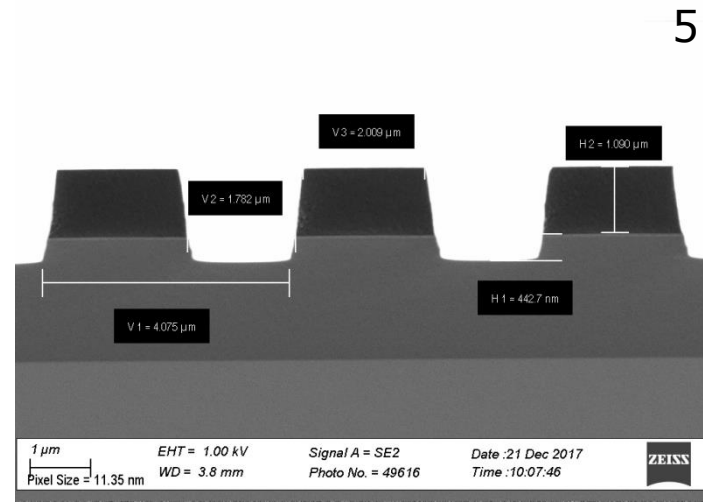
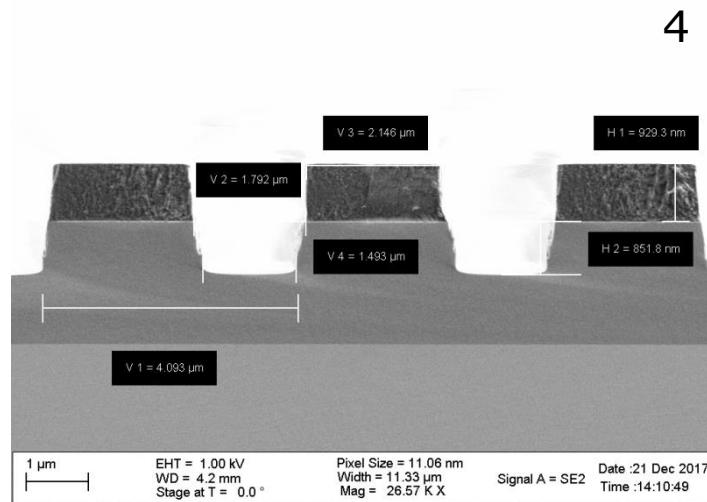
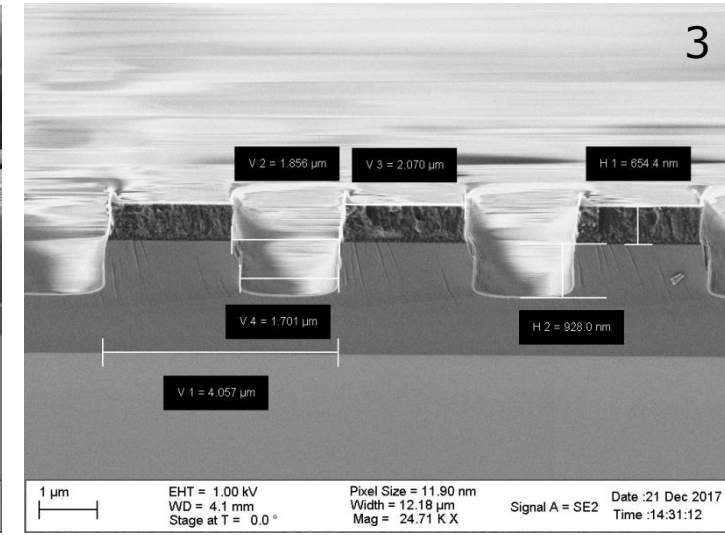
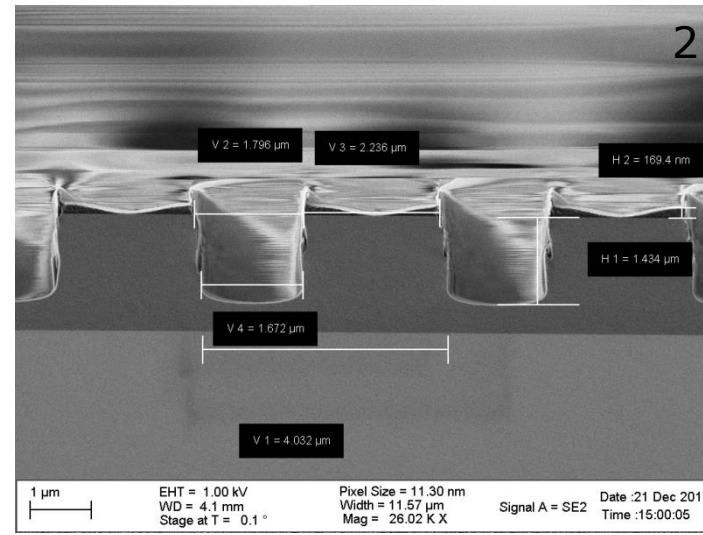
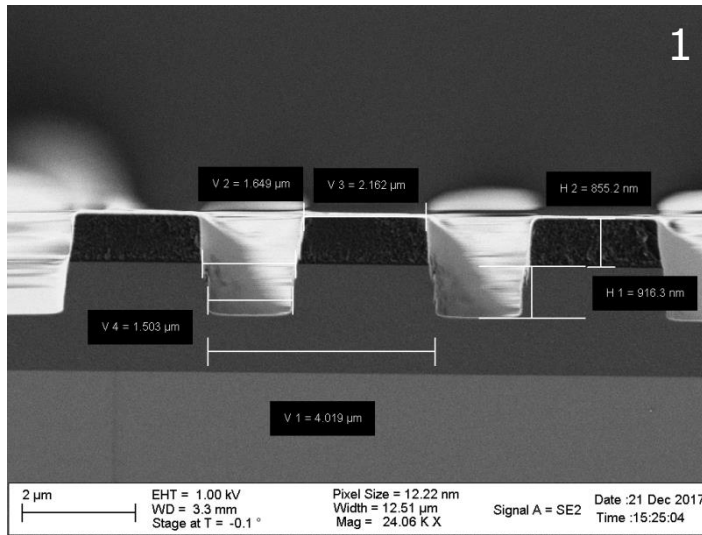


Zoom out - squares

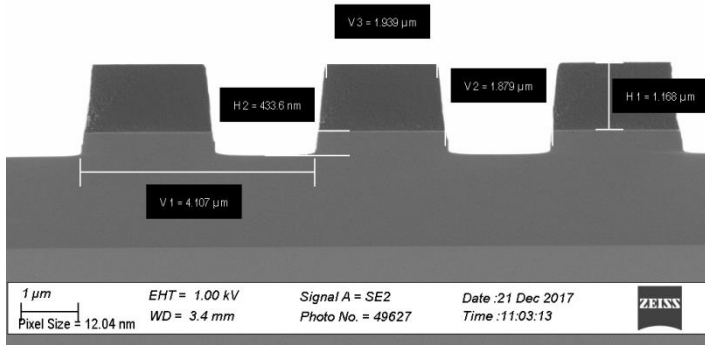


Zoom out - squares

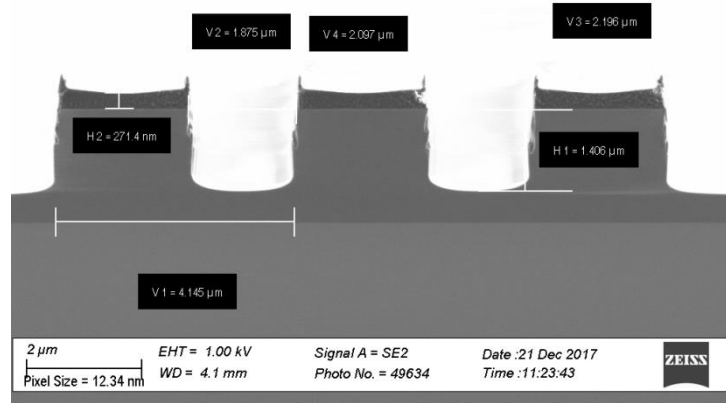
Etch Profiles with resist still on: experiments 1-16



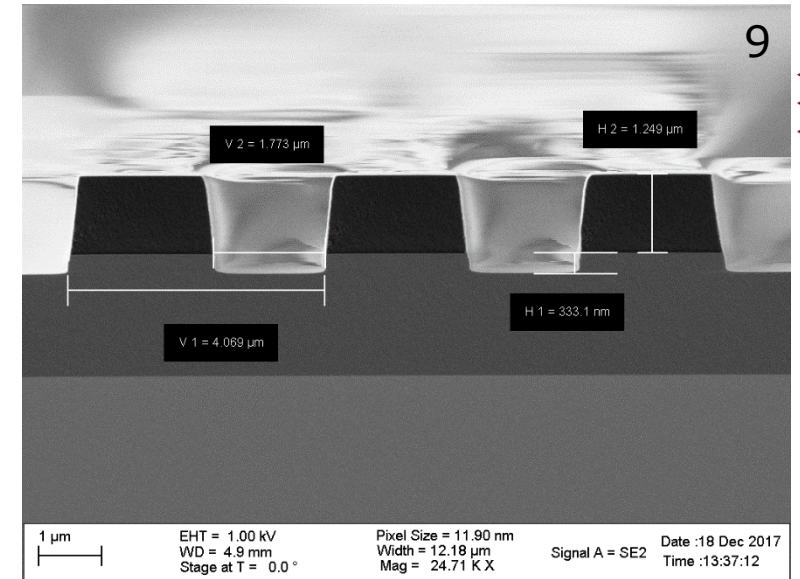
7



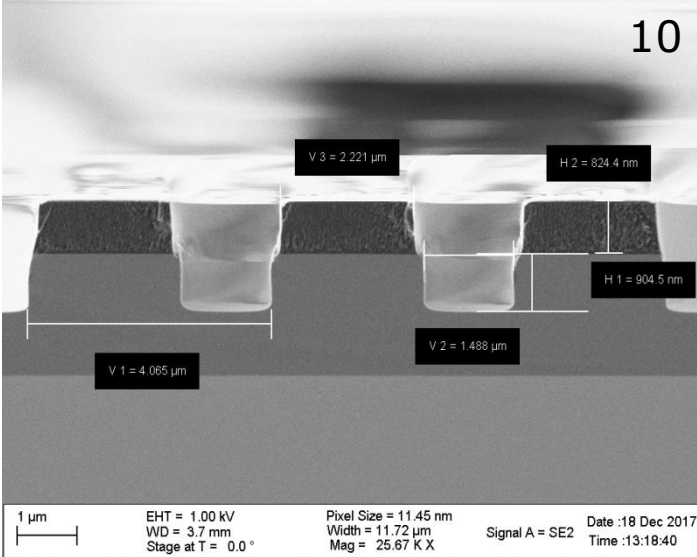
8



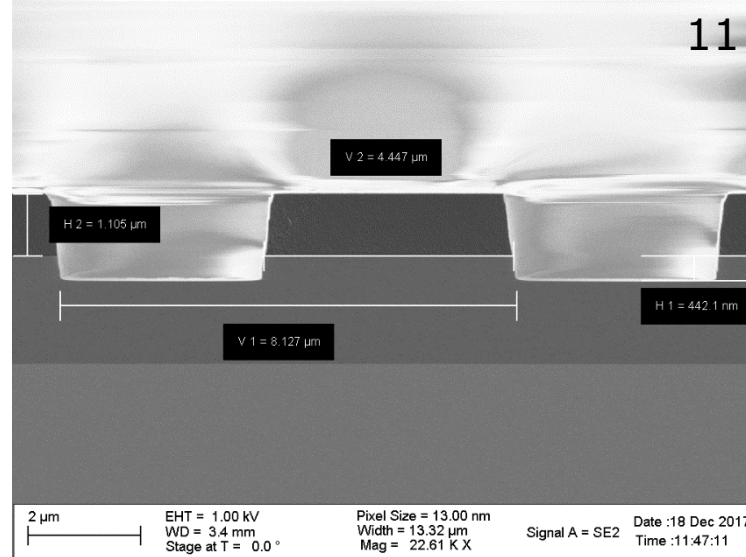
9



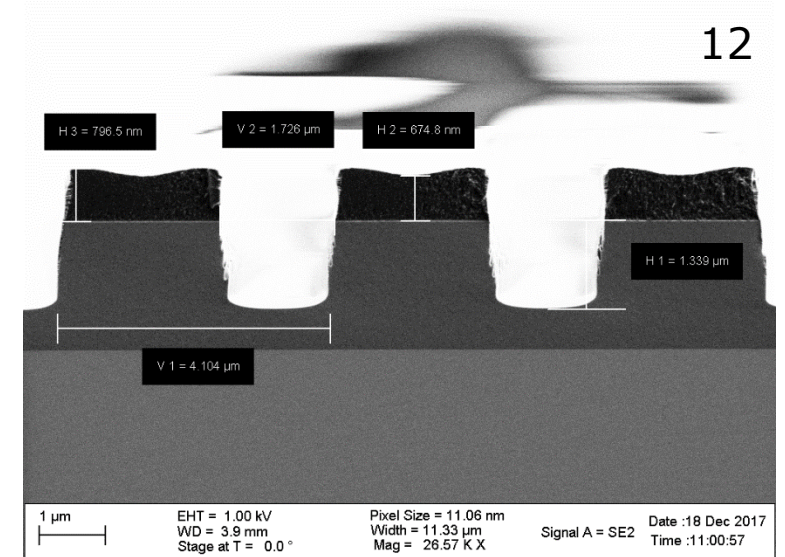
10



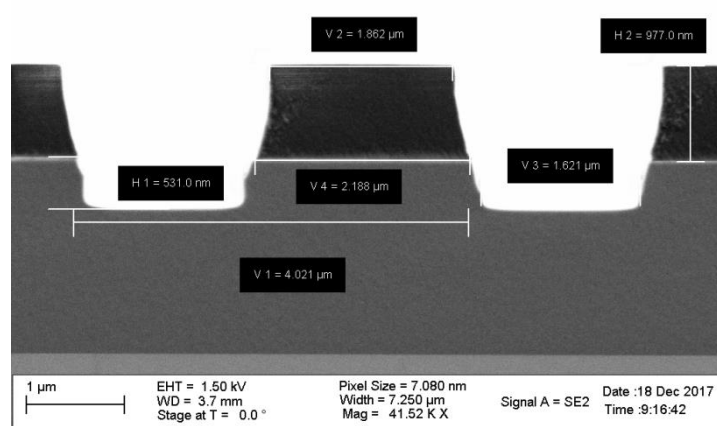
11



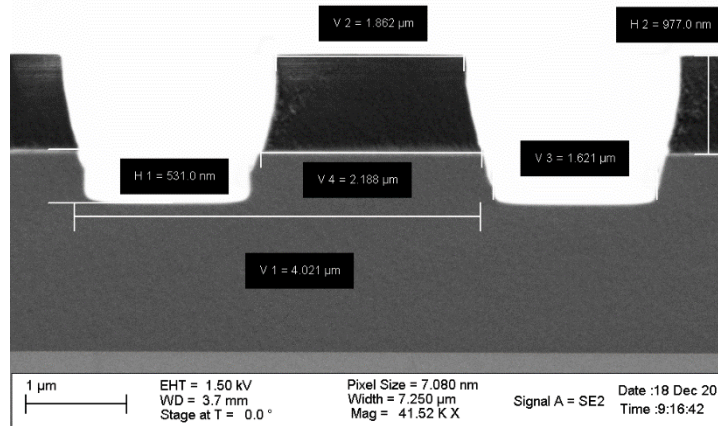
12



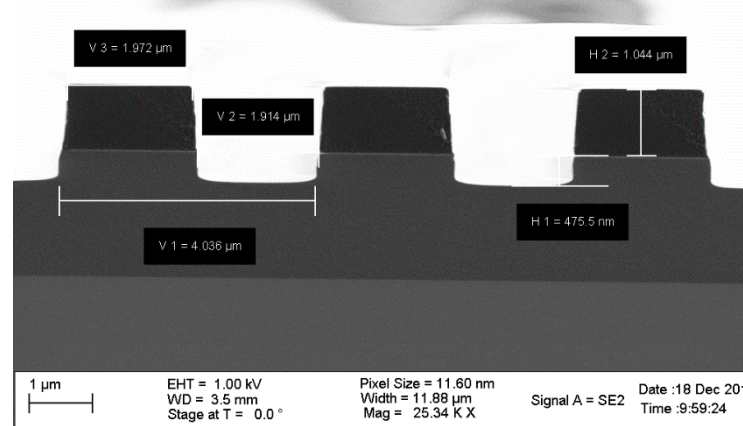
13



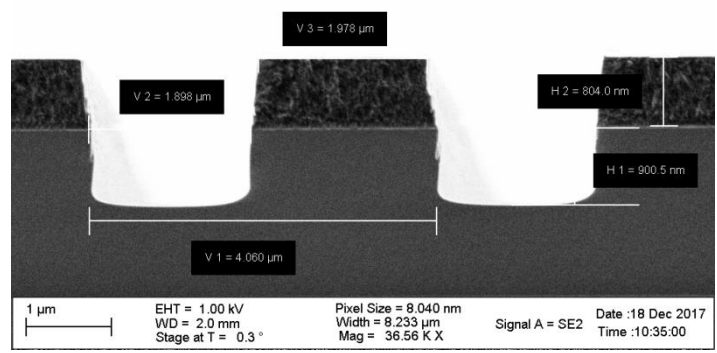
14



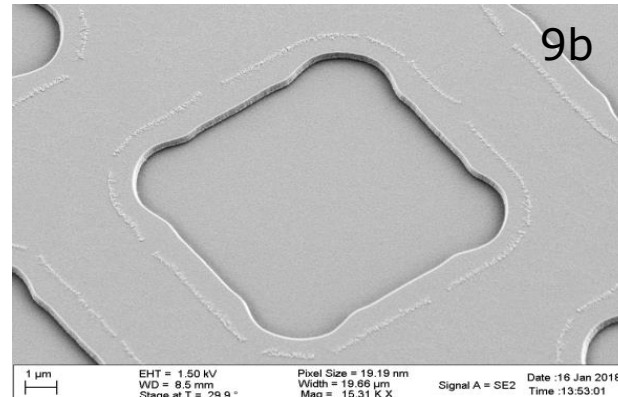
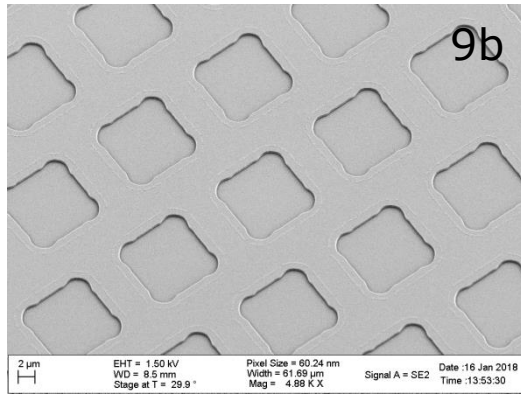
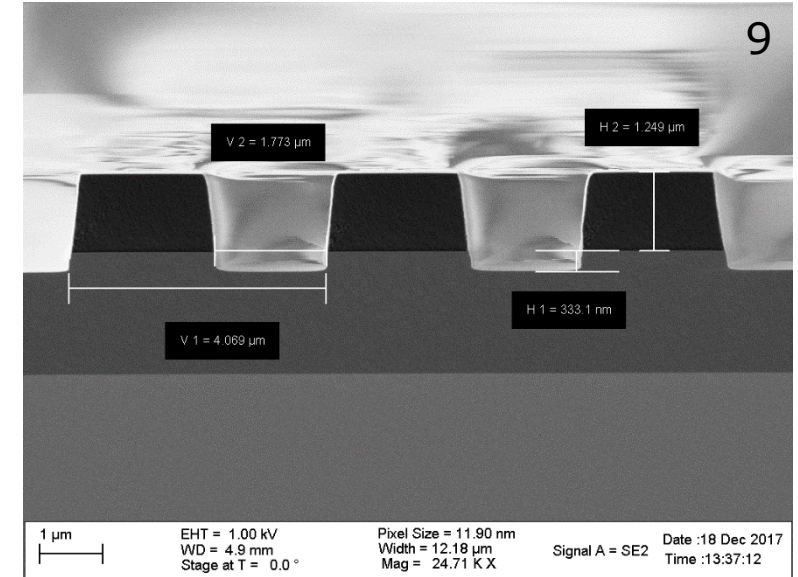
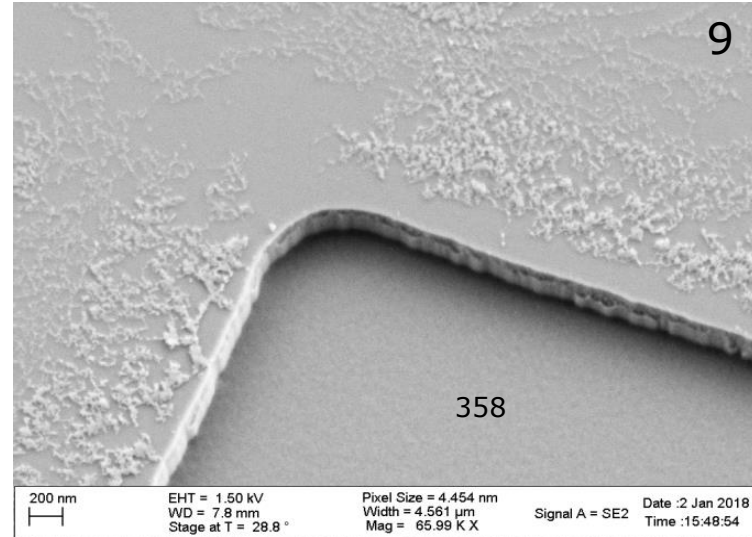
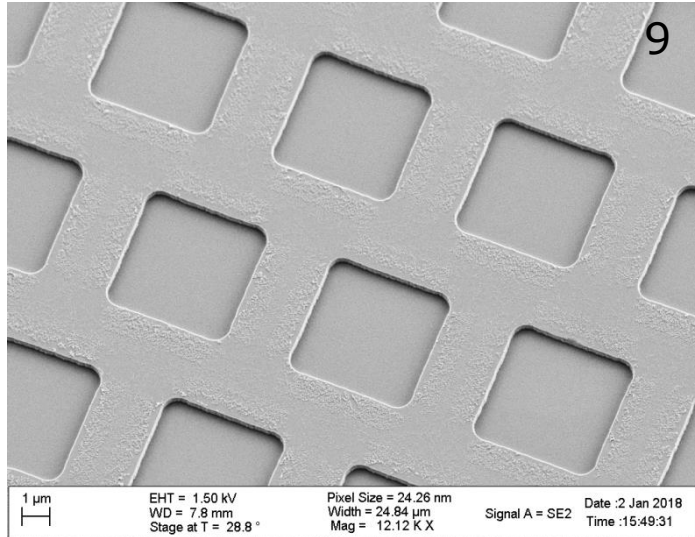
15



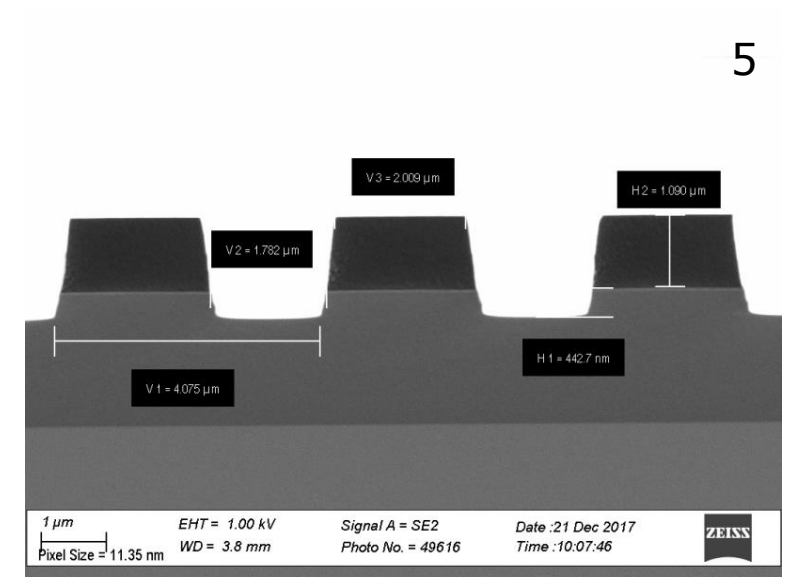
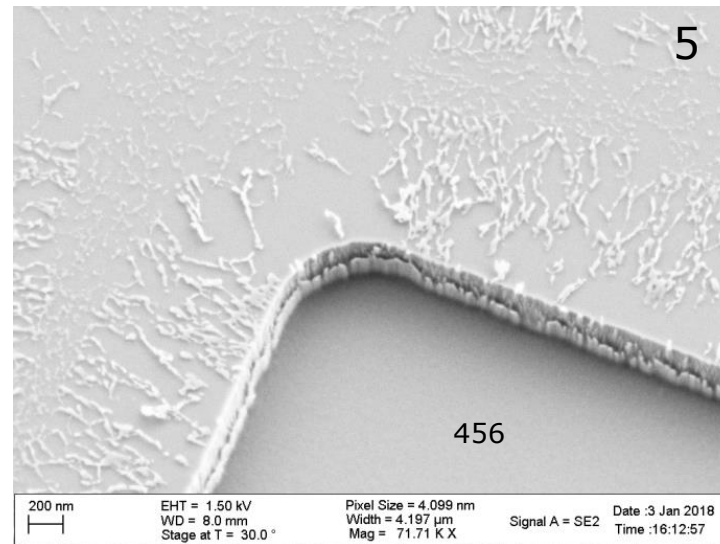
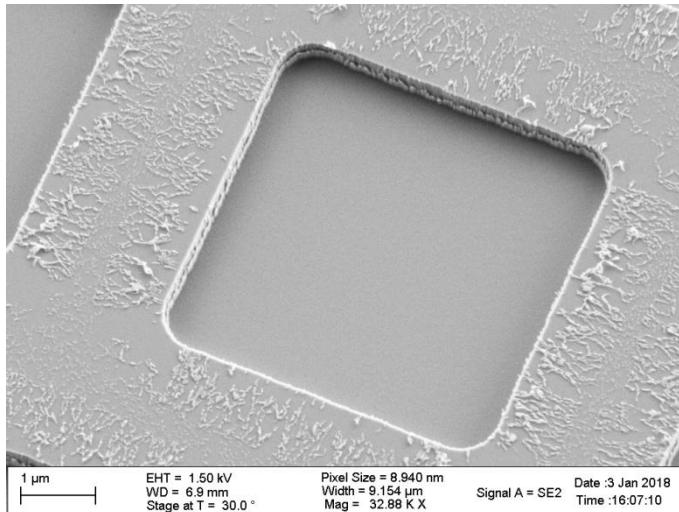
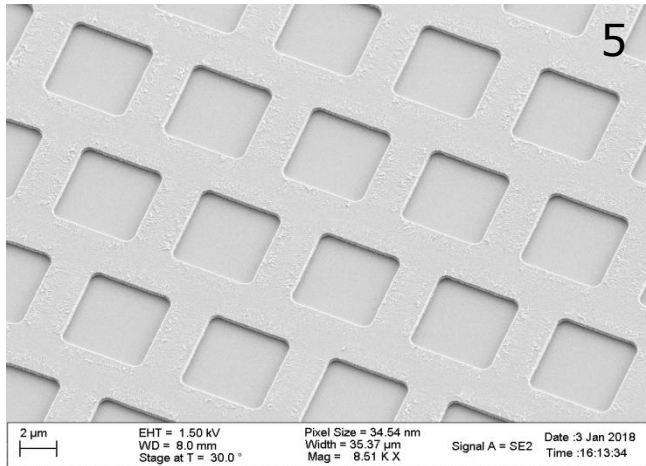
16



No 9 – least amount of re-deposition

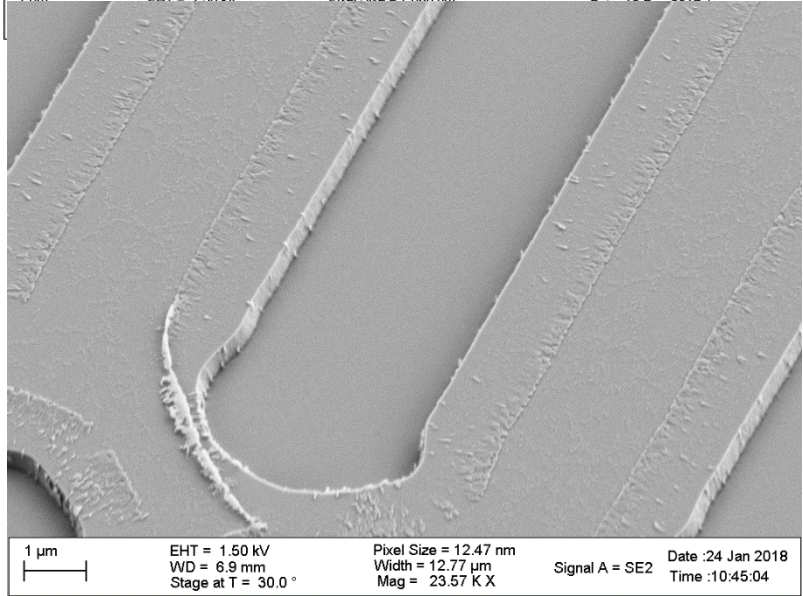
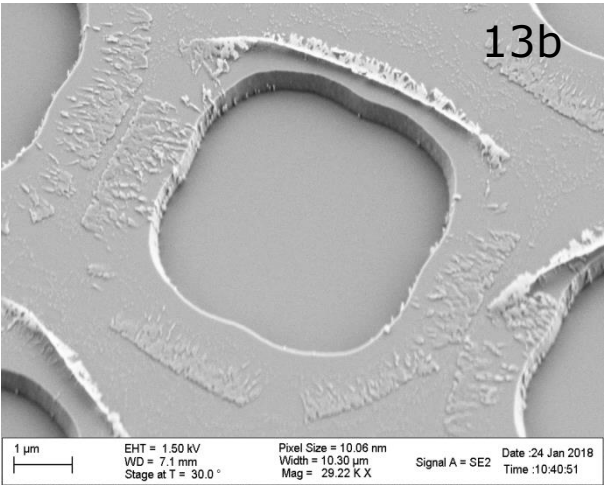
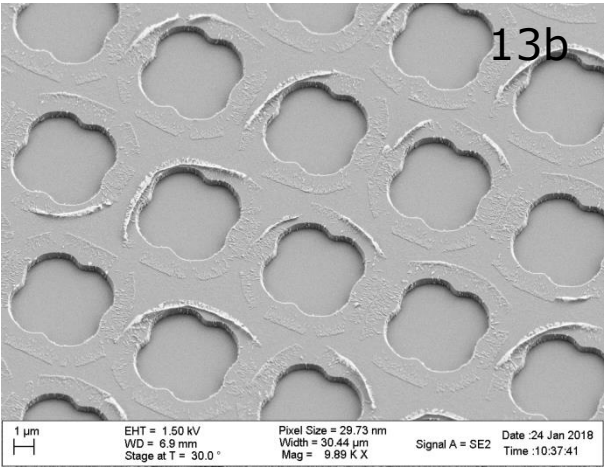
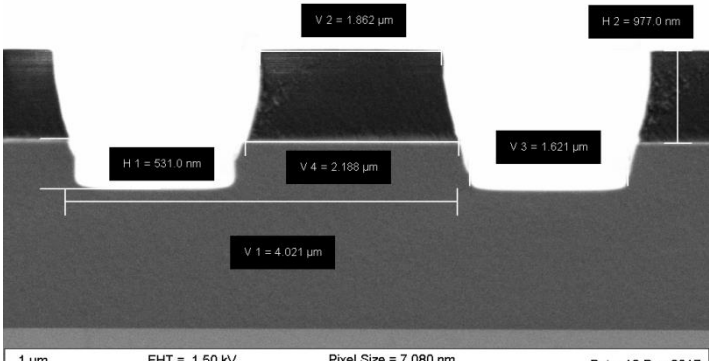
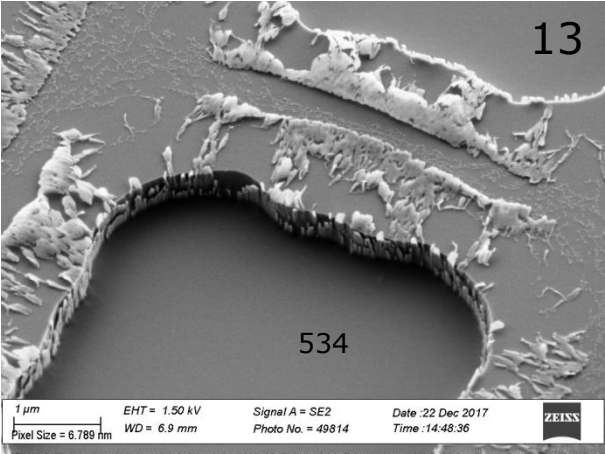
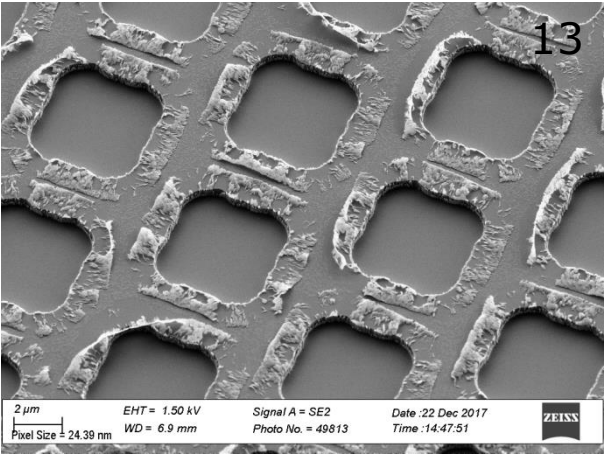


No 5

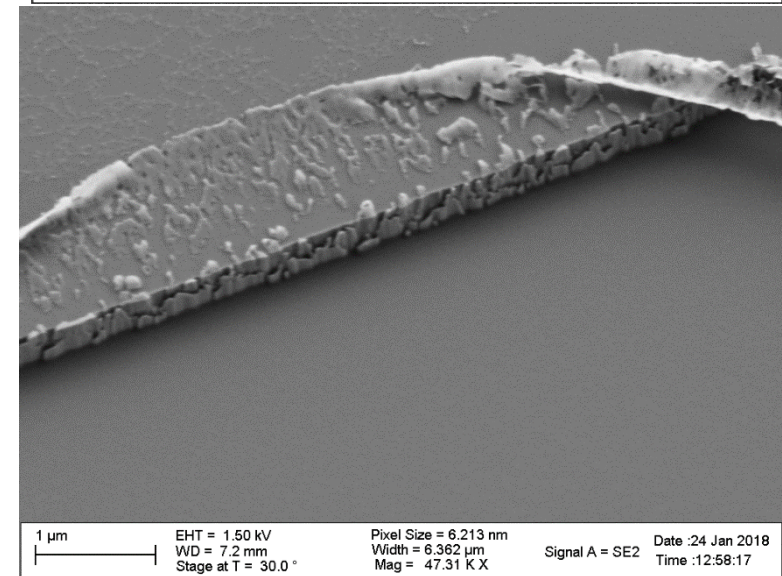
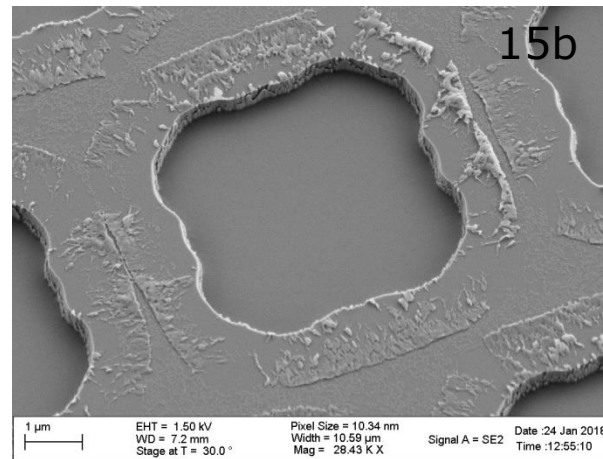
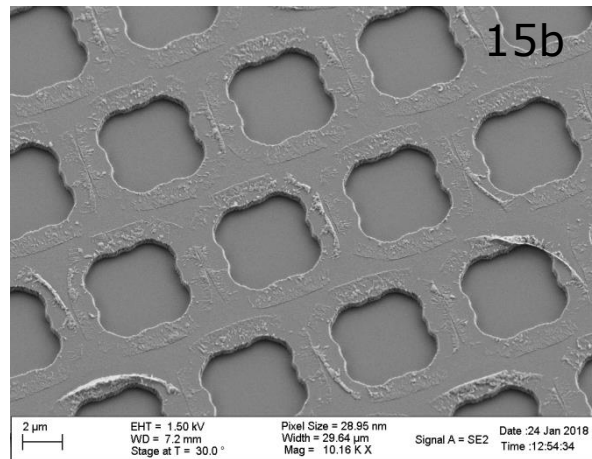
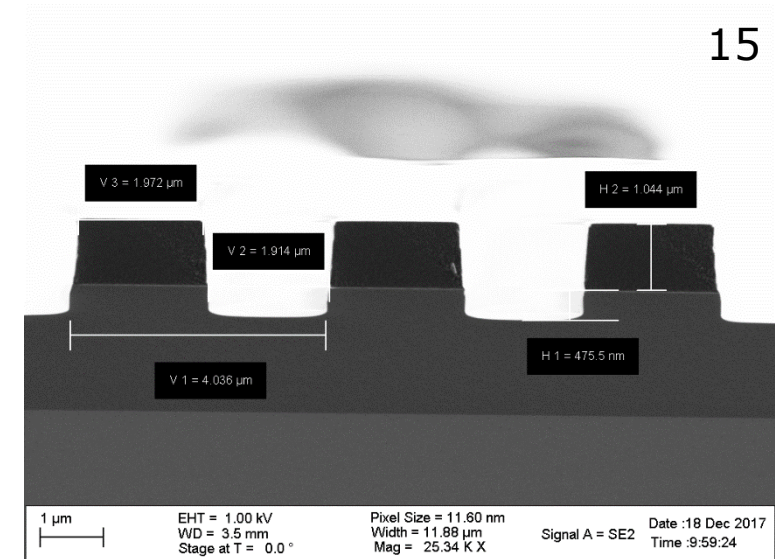
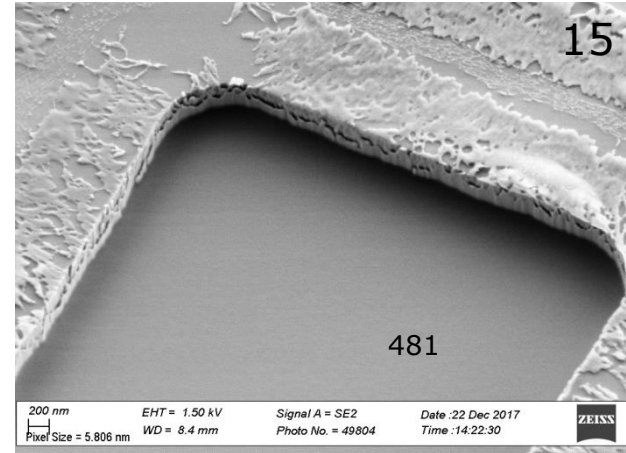
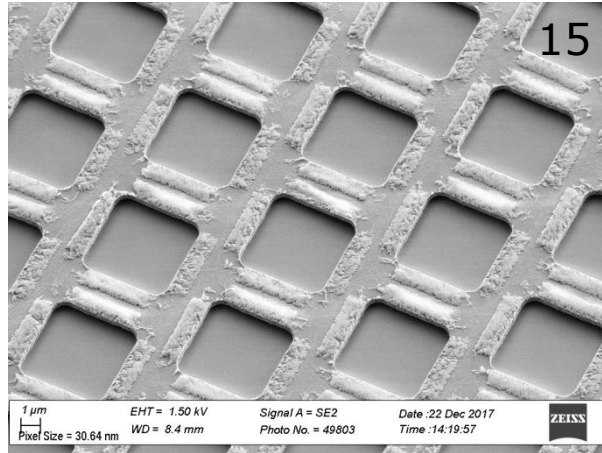


No 13

13

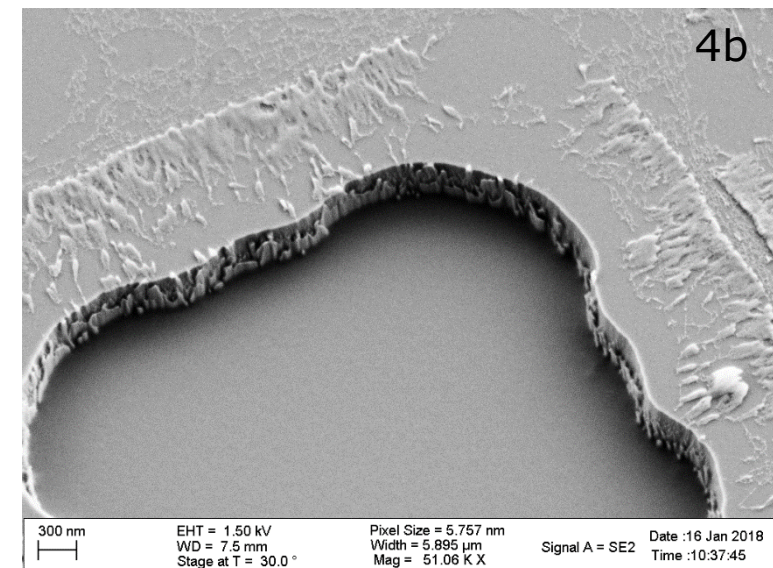
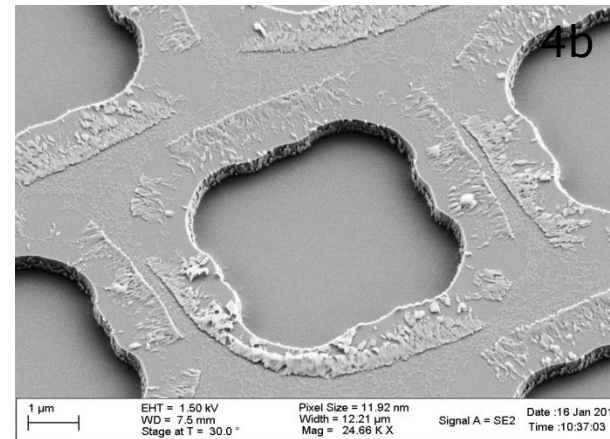
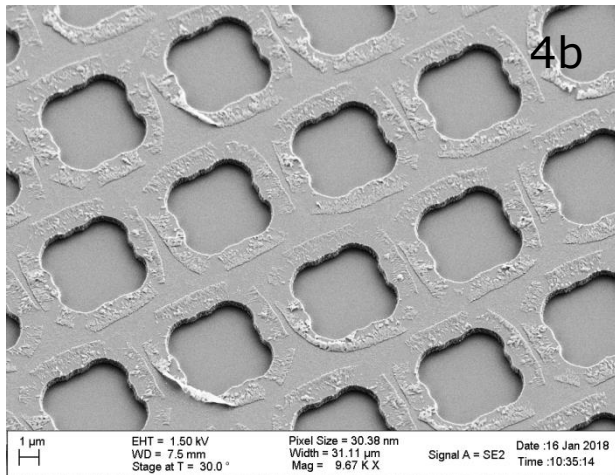
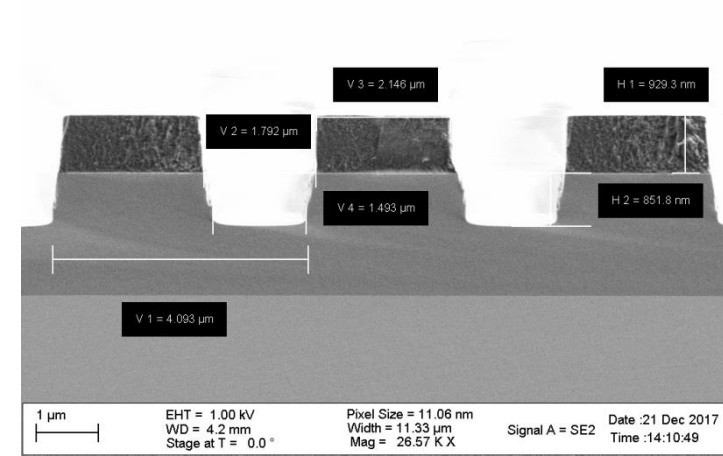
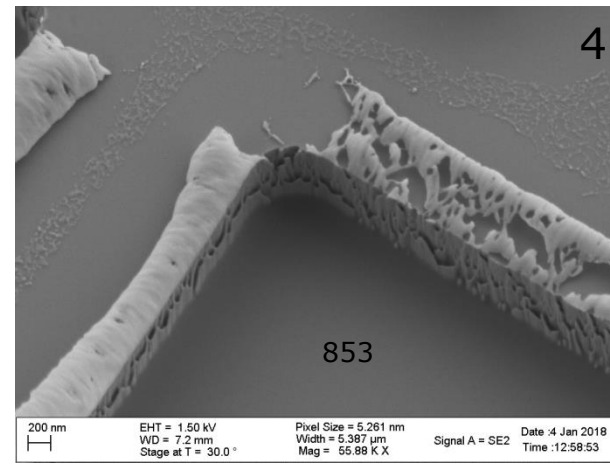
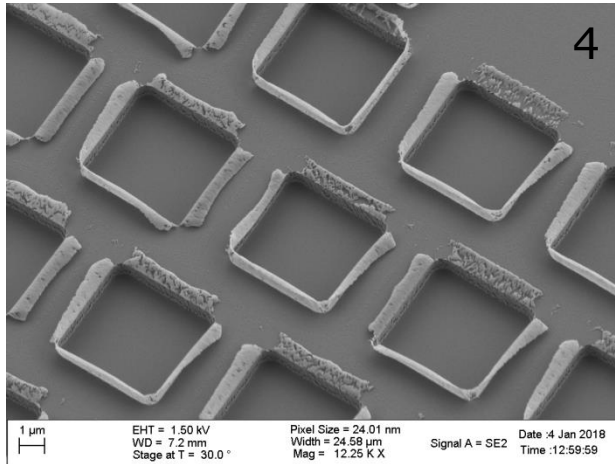


No 15



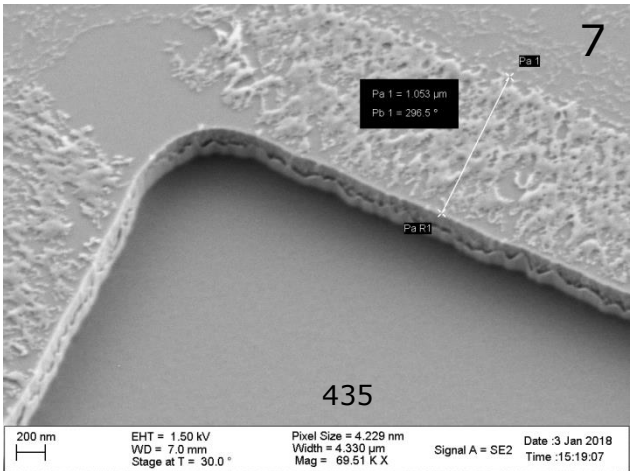
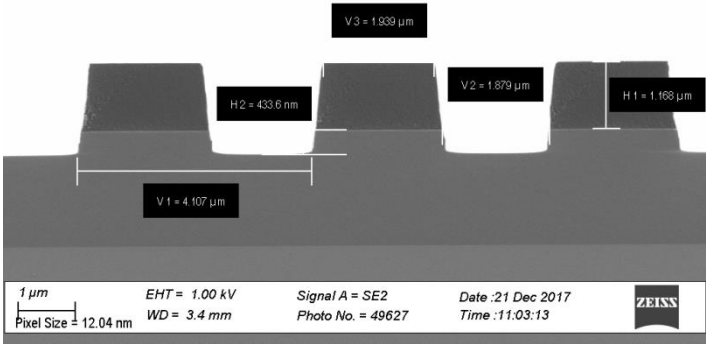
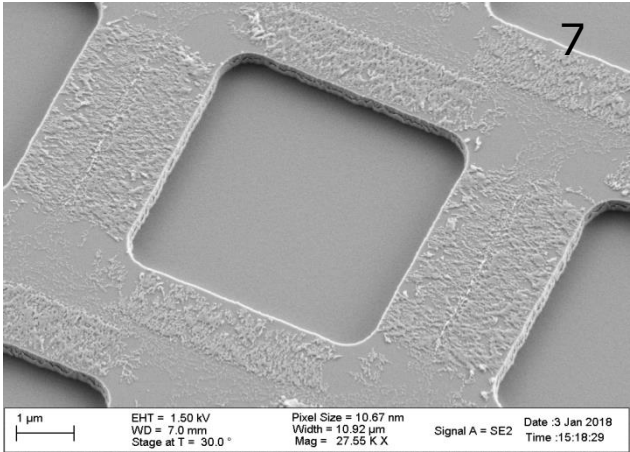
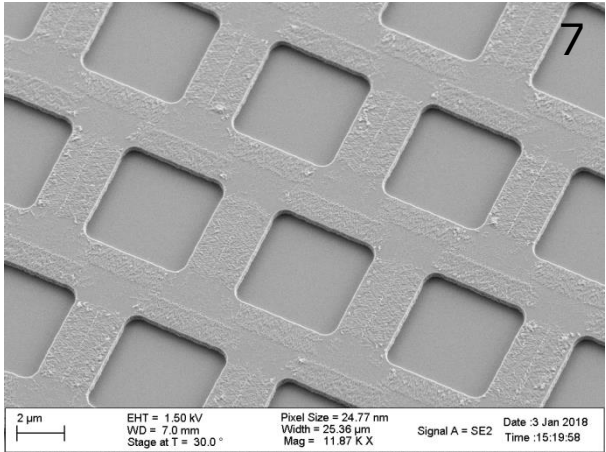
No 4

4



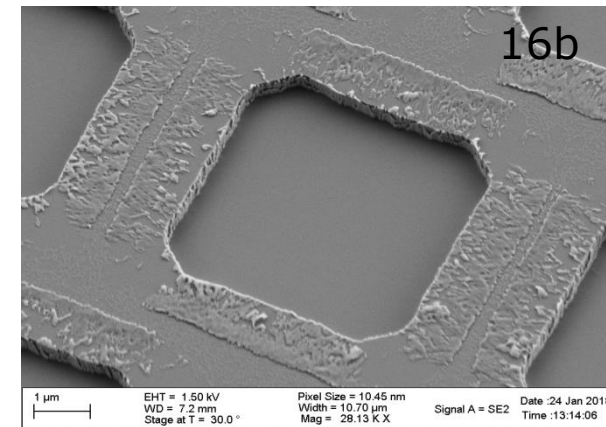
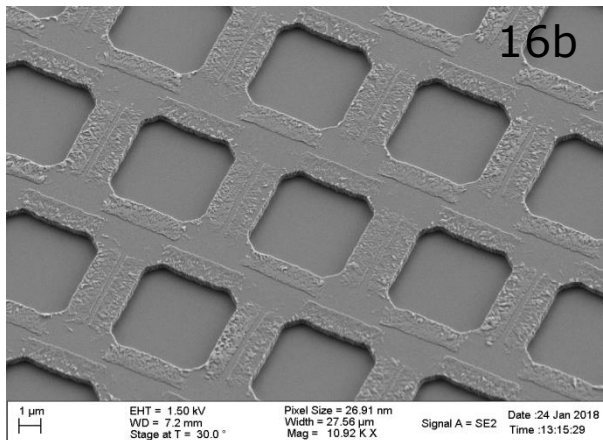
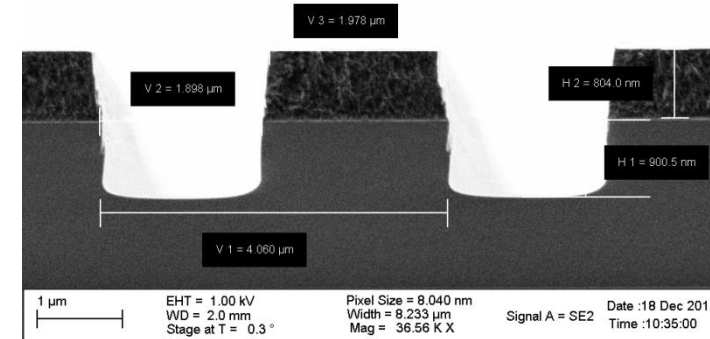
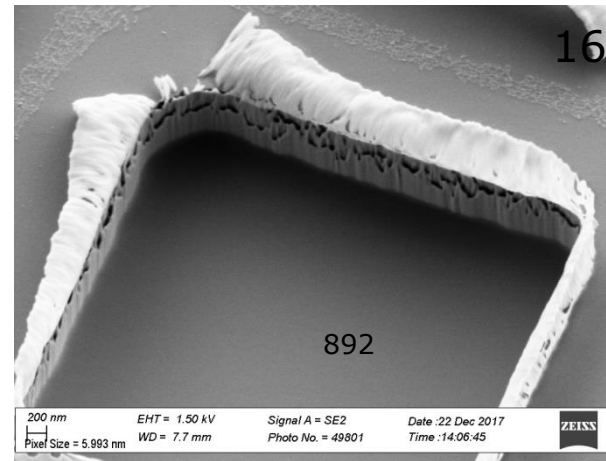
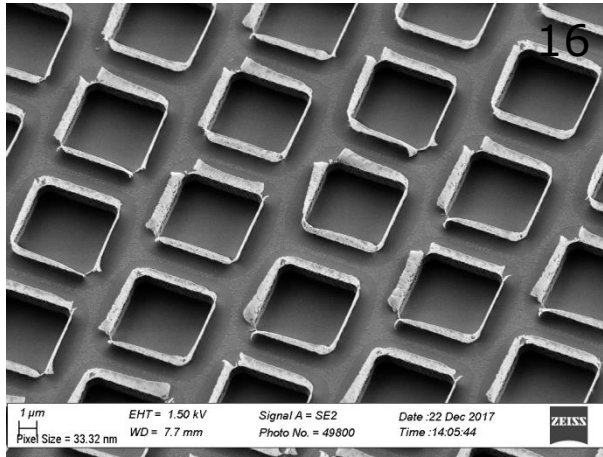
No 7

7

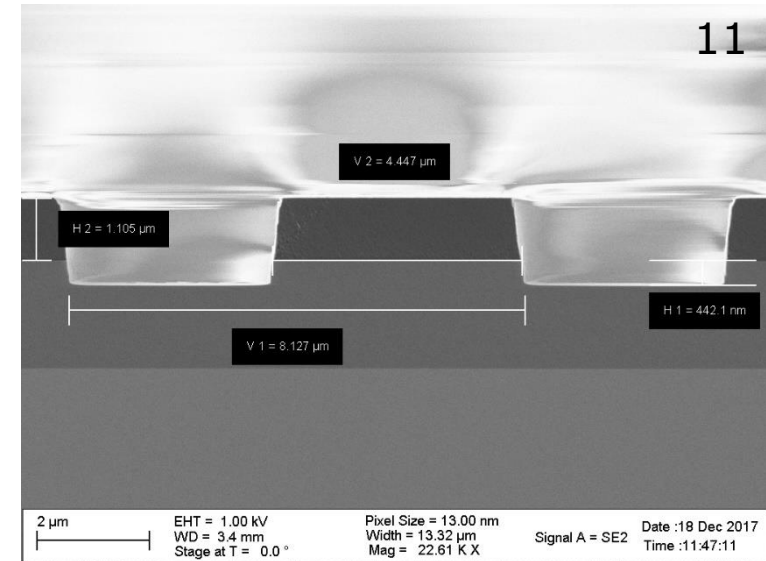
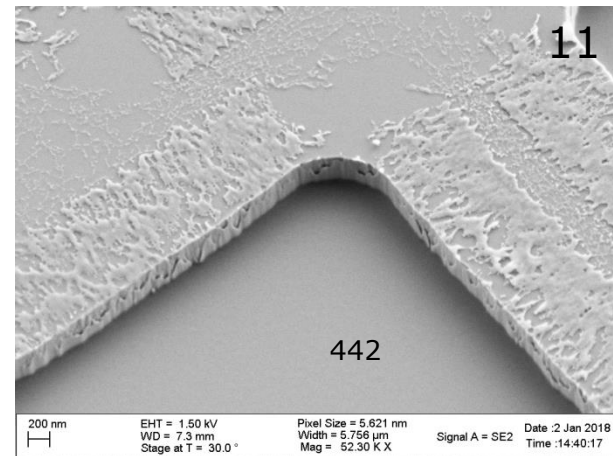
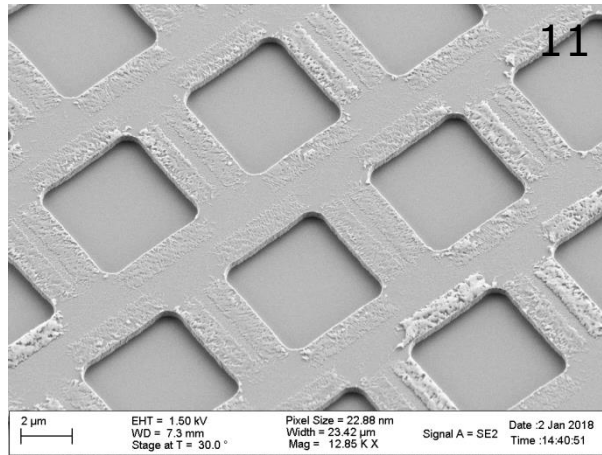


No 16

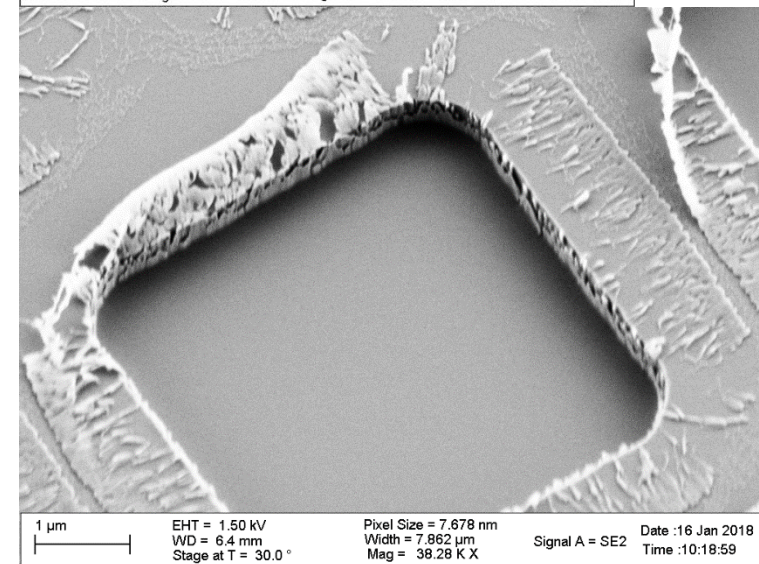
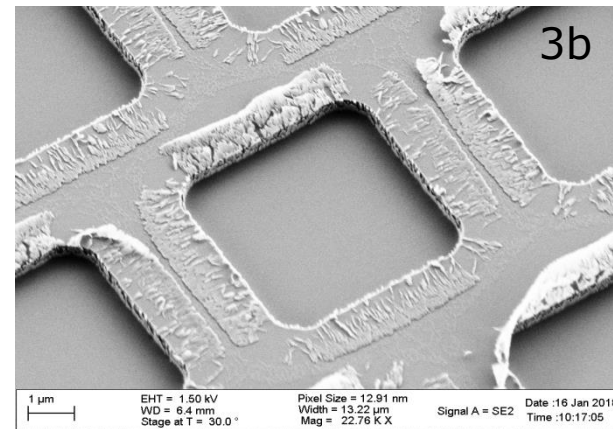
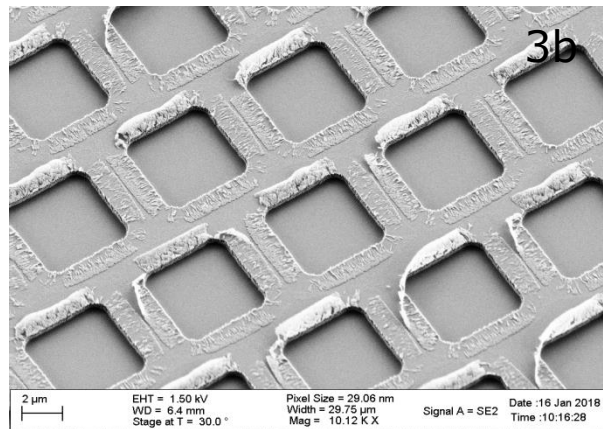
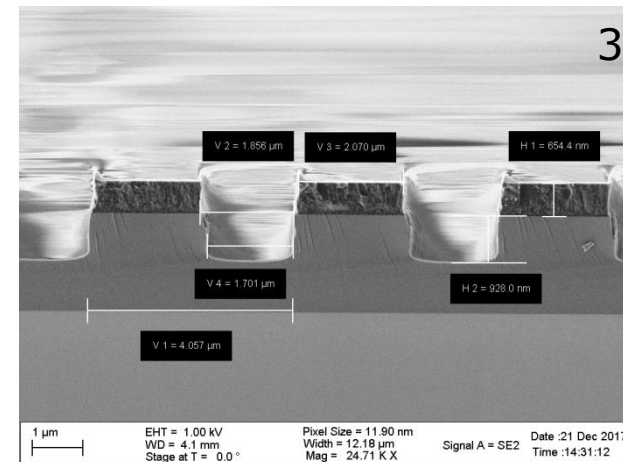
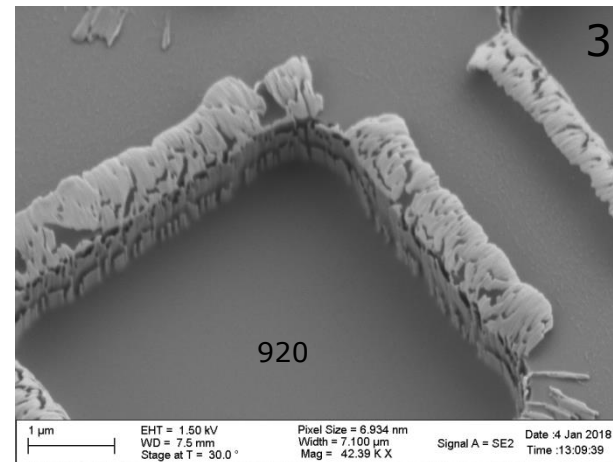
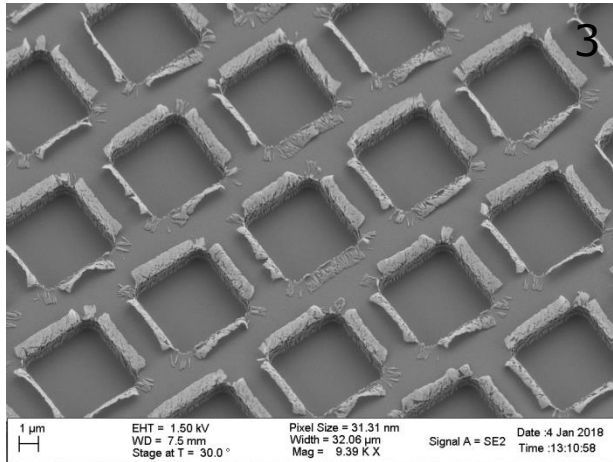
16



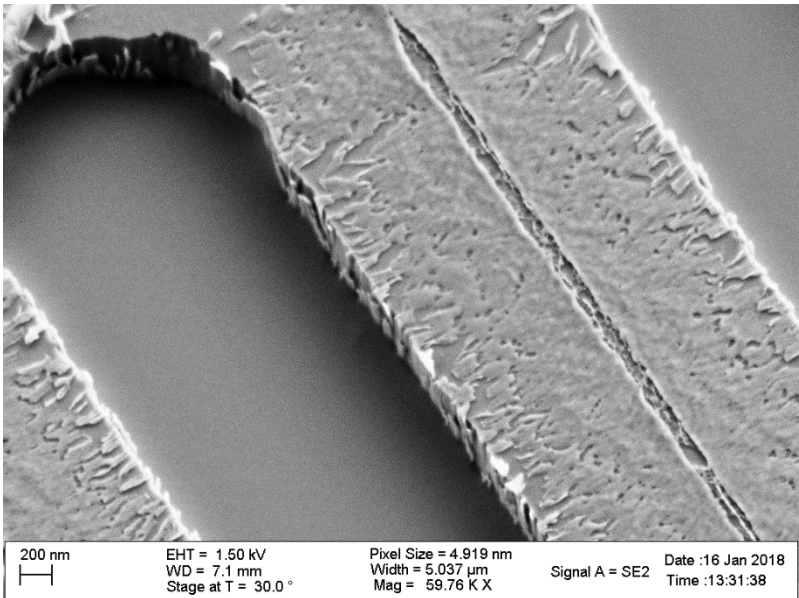
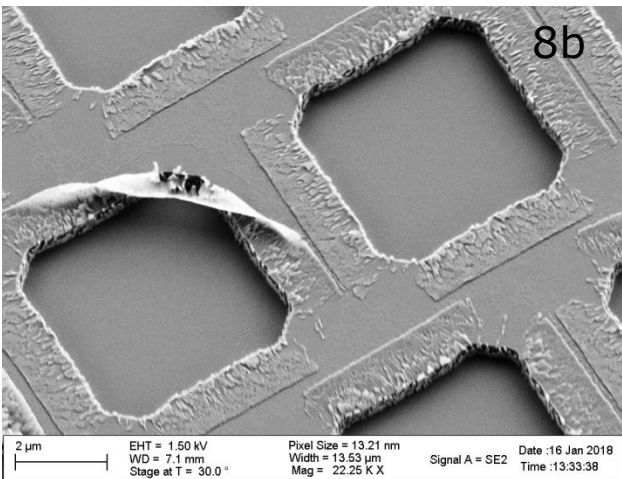
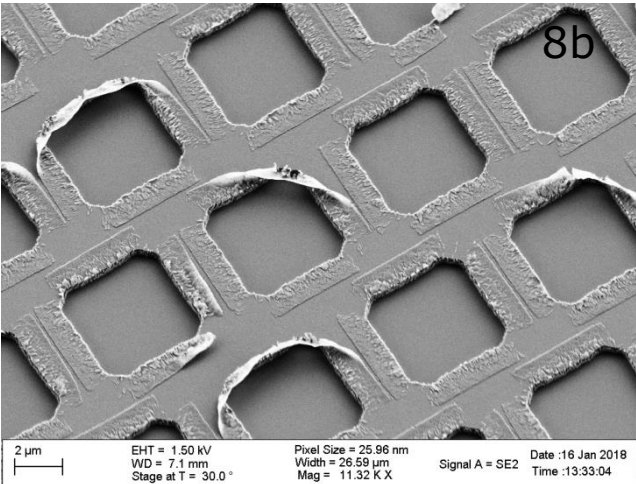
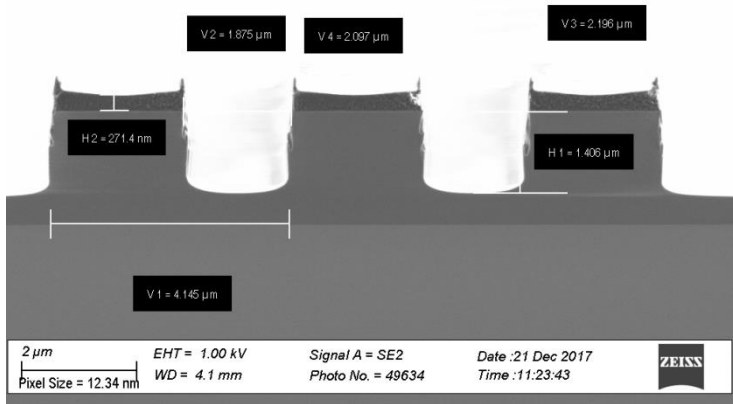
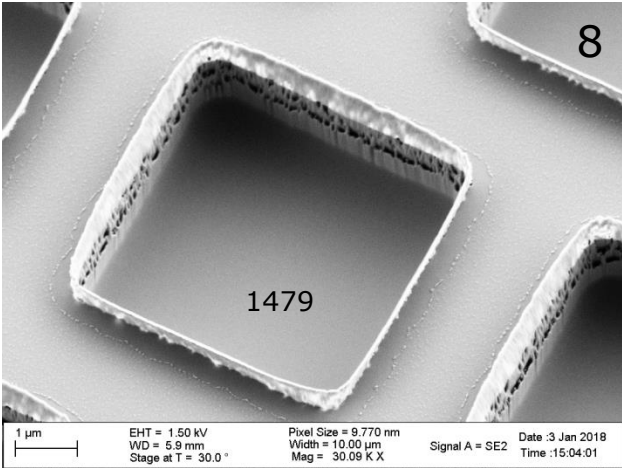
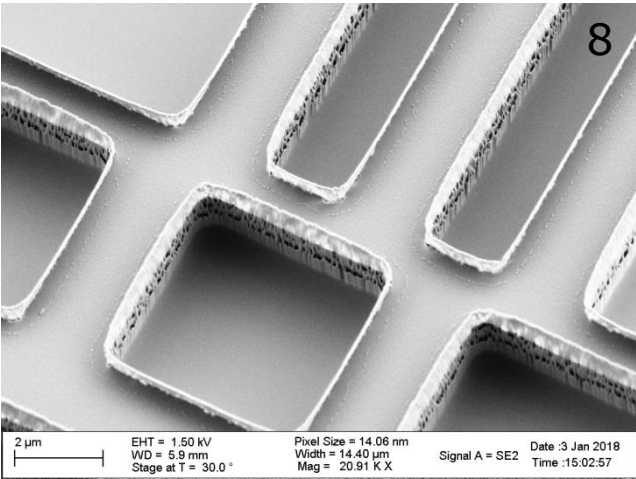
No 11



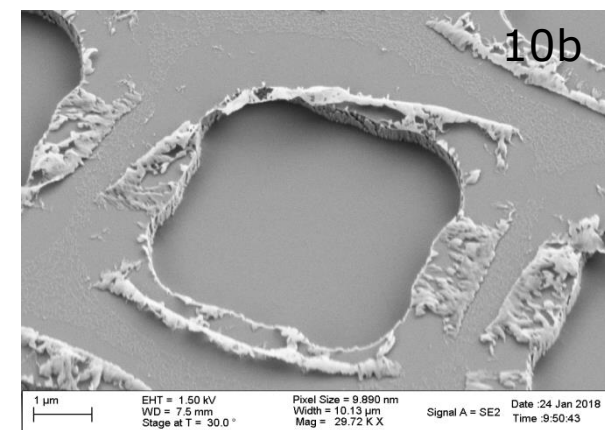
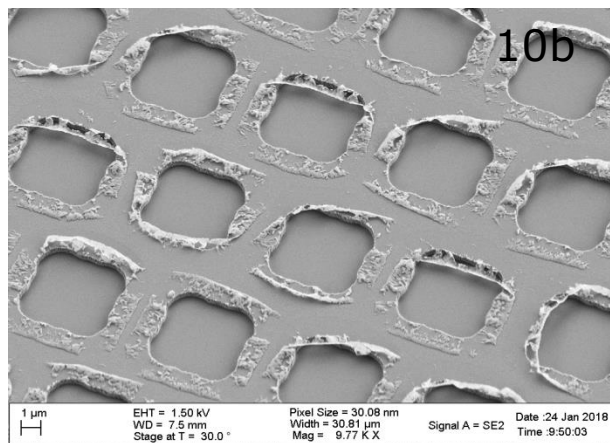
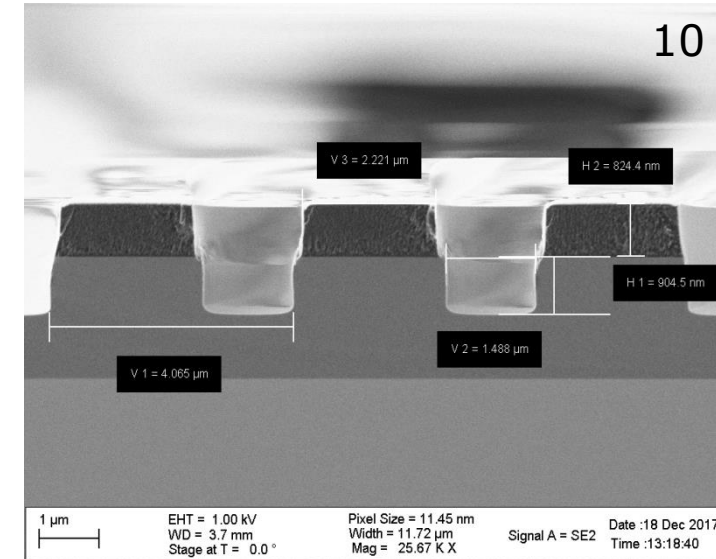
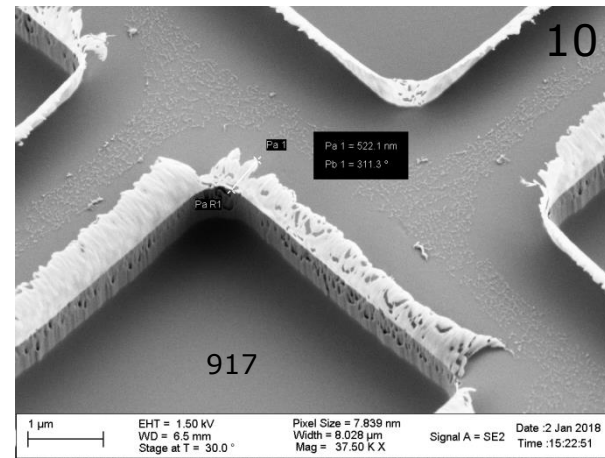
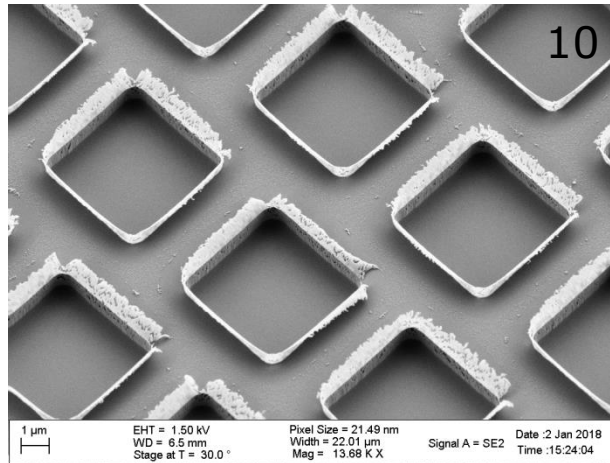
No 3



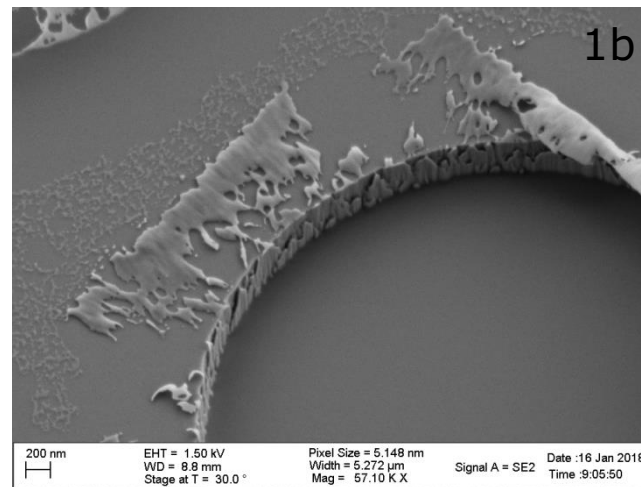
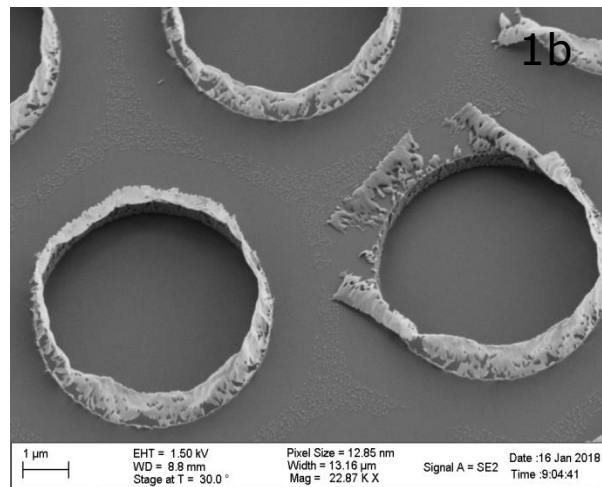
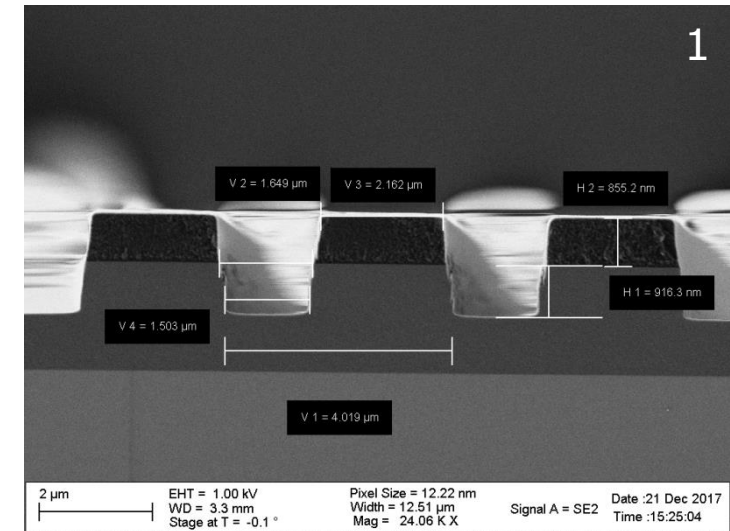
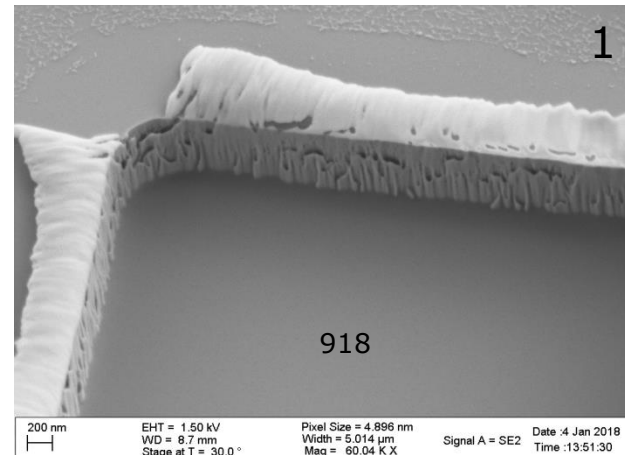
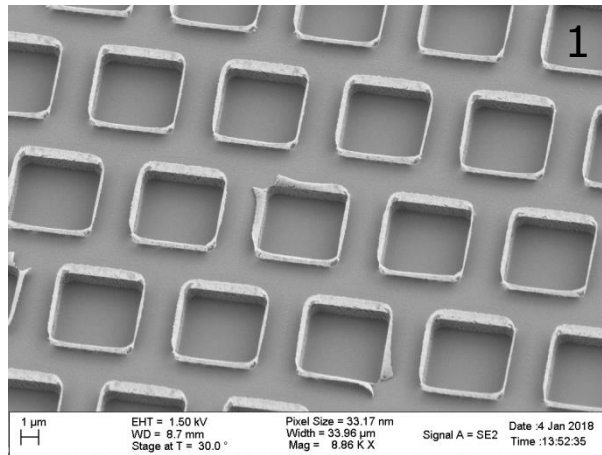
No 8



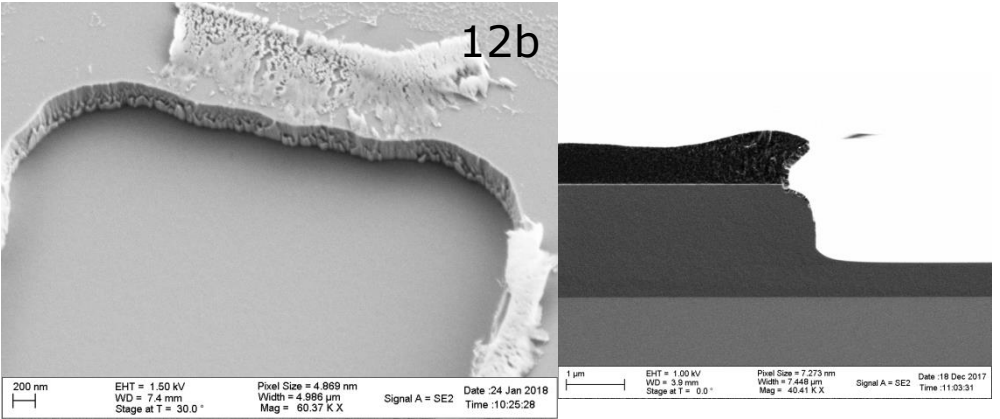
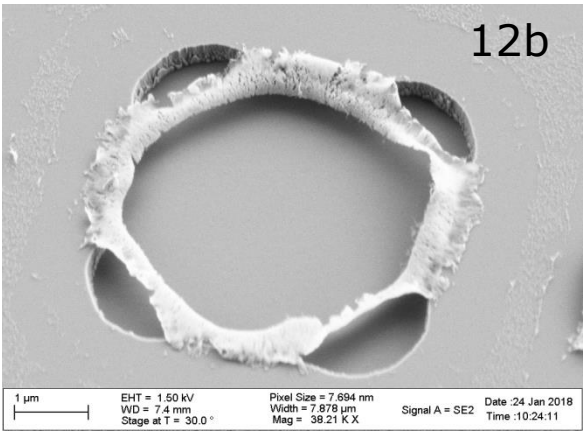
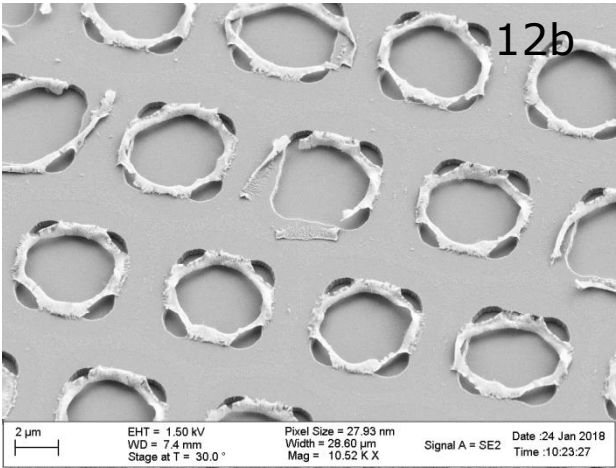
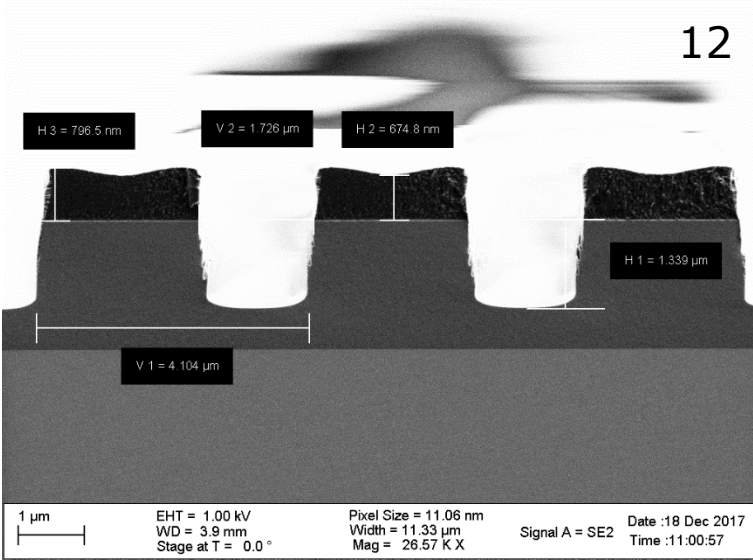
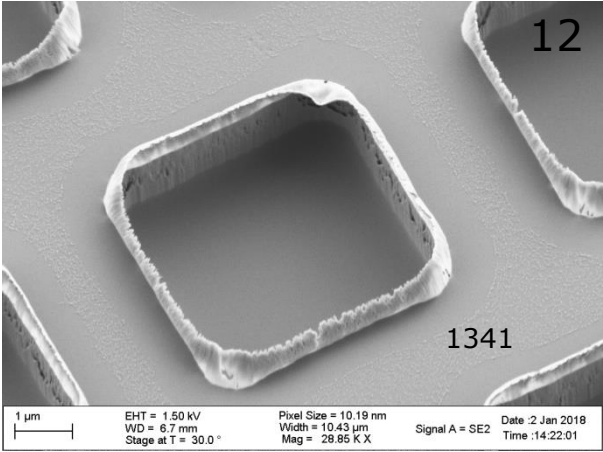
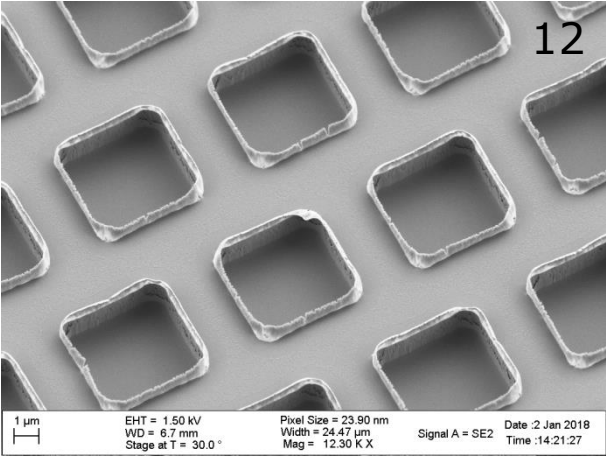
No 10



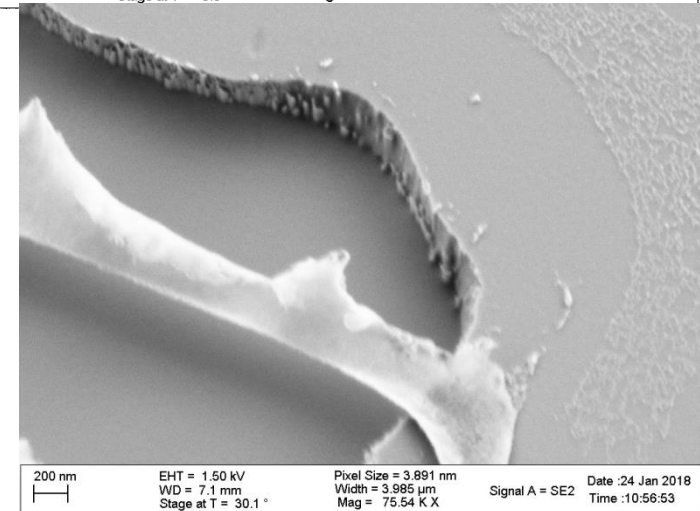
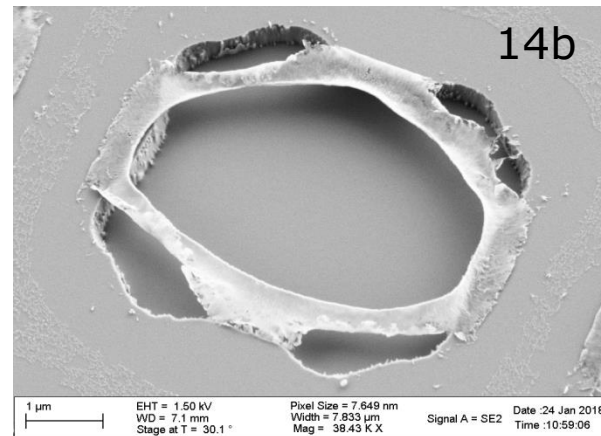
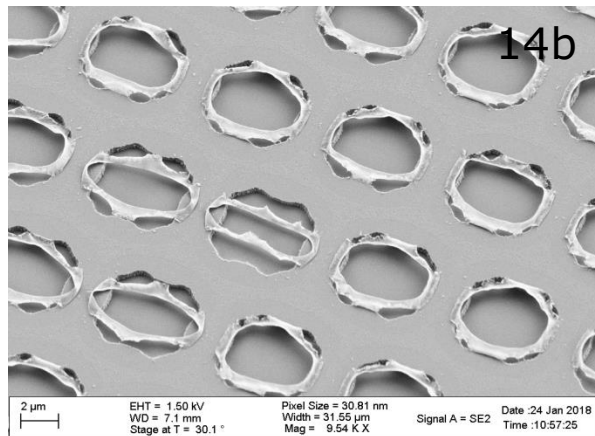
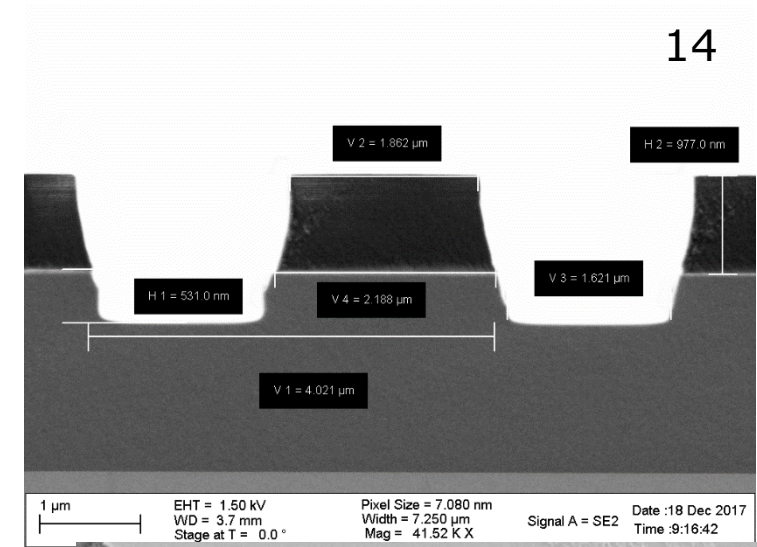
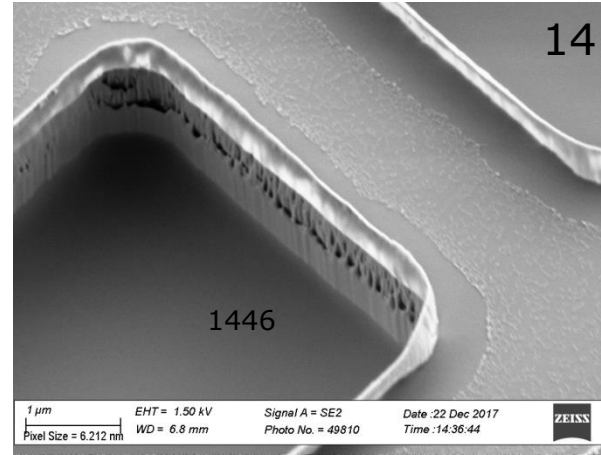
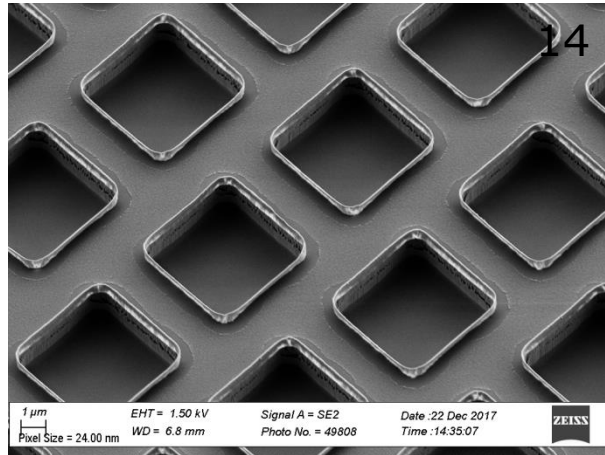
No. 1



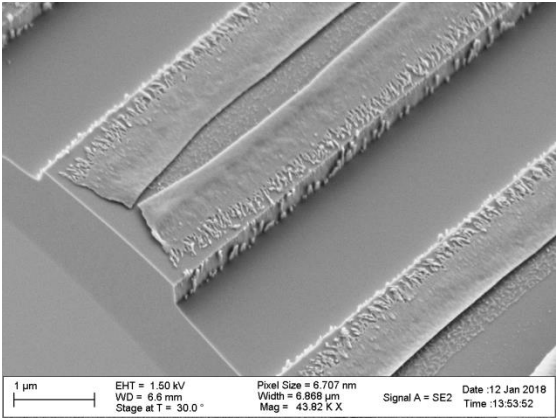
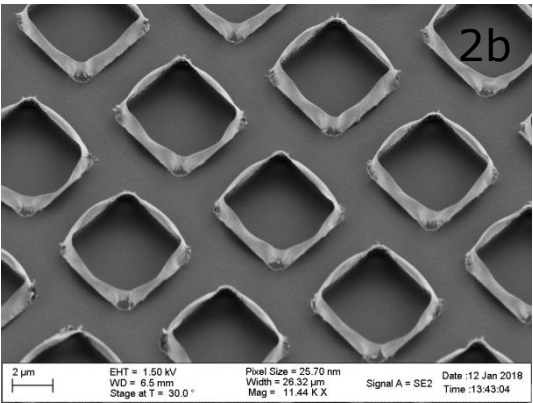
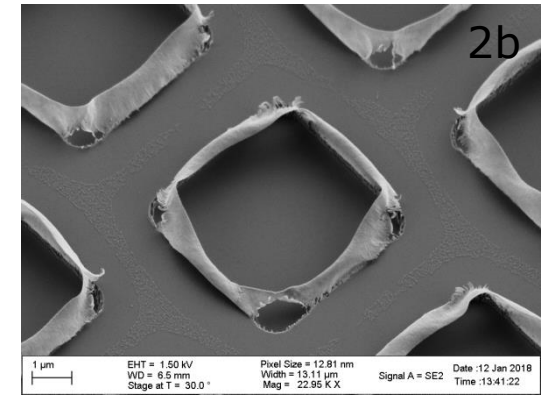
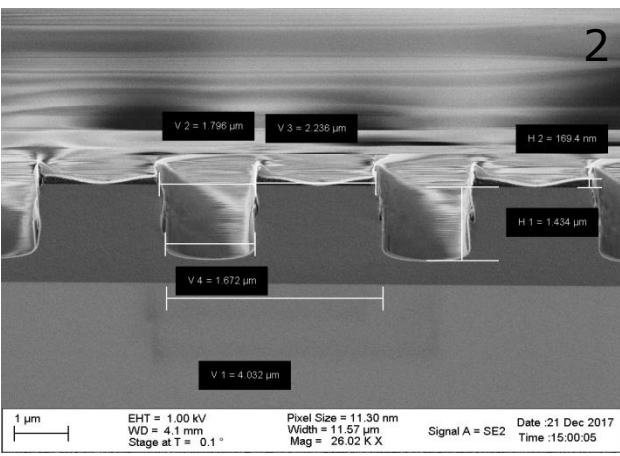
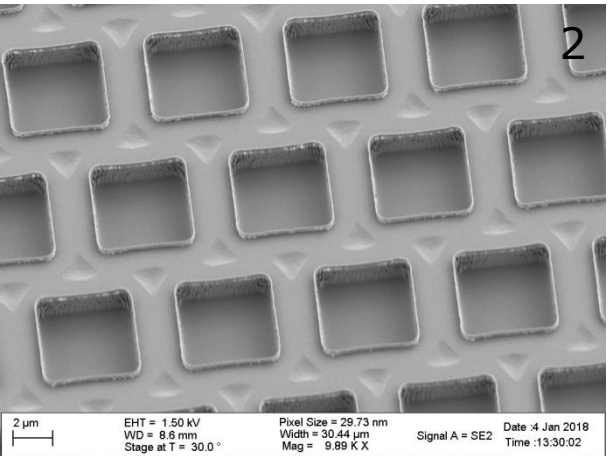
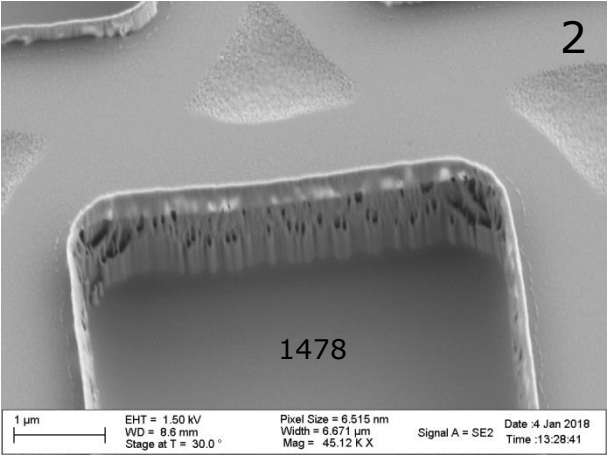
No 12



NO 14



No. 2



No 6 largest amount of re-deposition left

